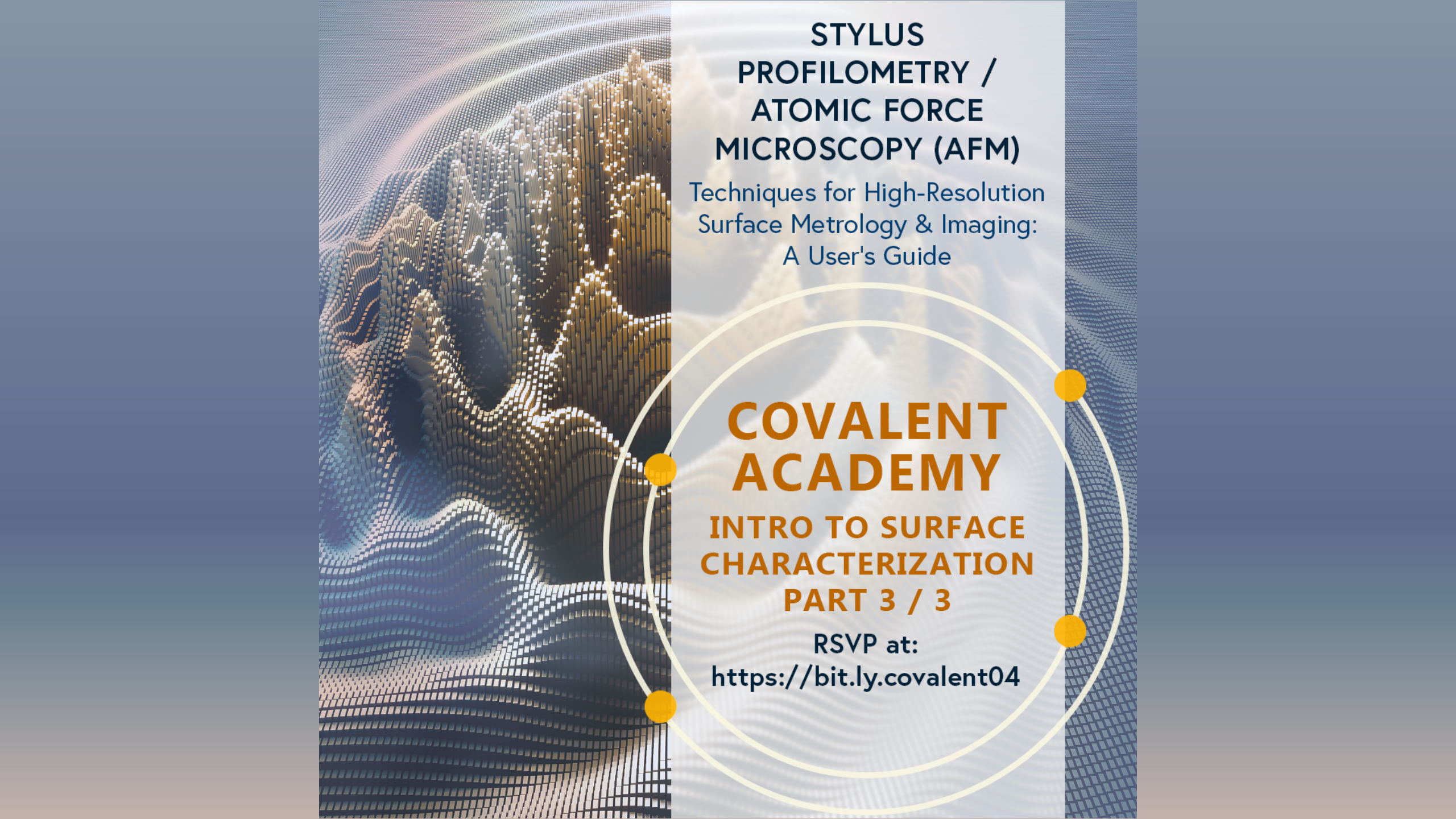




# STYLUS PROFILOMETRY / ATOMIC FORCE MICROSCOPY (AFM)

Techniques for High-Resolution  
Surface Metrology & Imaging:  
A User's Guide

## COVALENT ACADEMY

INTRO TO SURFACE  
CHARACTERIZATION  
PART 3 / 3

RSVP at:  
<https://bit.ly.covalent04>



- Founded 2016
- Testing, measurement & characterization Platform
- 30 team members (13 PhDs)
- 9,500 ft<sup>2</sup> lab in Sunnyvale
- 1-Stop-Shop Source for Answers
  - 30 instruments in-house
  - 6 partnerships with instrument makers
  - 11 partner labs
  - 6 corporate “tool shares”
- **>275 customers** (80% repeat)



[hello@covalentmetrology.com](mailto:hello@covalentmetrology.com)

## Electron & Scanning Probe Microscopy

*(SEM/TEM, AFM, EDS, EELS, Nanoindent, acoustic microscopy)*

## Surface Analysis

*(XPS, Auger, ToF-SIMS, dSIMS)*

## Optical Microscopy & Spectroscopy

*(Laser Confocal, White Light, Chromatic Dispersion, Spectral Ellipsometry, UV-Vis-NIR Spectroscopy)*

## Materials/PC Board FA

*(Cross Sections, Inspections, Dye & Pry)*

## X-Ray Characterization

*(XRD/XRR, XRF,  $\mu$ CT)*

## Chemical Analysis

*(ICPMS, GCMS, FTIR, Raman, Solid & Solution NMR, 2D NMR)*

## Nanoparticle Analysis

*(DLS, PSA, Particle Zeta Potential)*

## Bulk Properties Characterization

*(DSC, TGA, DMA, Rheometry, Tensile Test, Pencil Test, Surface Zeta Potential)*



Austin Barnes is an expert physical chemist with over 8 years of experience in scanning probe microscopy of ionomer materials and organic semiconducting nanostructures. He completed a PhD at the University of California in Santa Barbara, where his research incorporated specialized nanomechanical and conductive AFM probe measurements. He has published multiple articles in the field of charge transport of nanomaterials. Austin brings extensive knowledge of a wide range of scanning probe methodologies to his leadership of Covalent's stylus metrology team

Find Austin on [LinkedIn](#)

<https://www.linkedin.com/in/austin-barnes-84012953>

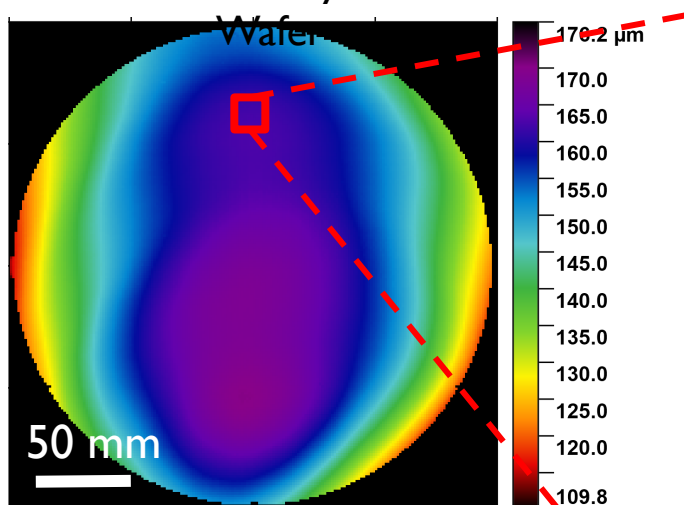


- Stylus Profilometry: The Pros and Cons
- Background AFM
- How to Choose the Right Tip?
- Common Scan Artifacts and How to Fix Them
- What Scan Size Should I Choose?
- What AFM should I use?

# Narrowing the Scope: AFM Looks at a Small FOV with Atomic Resolution

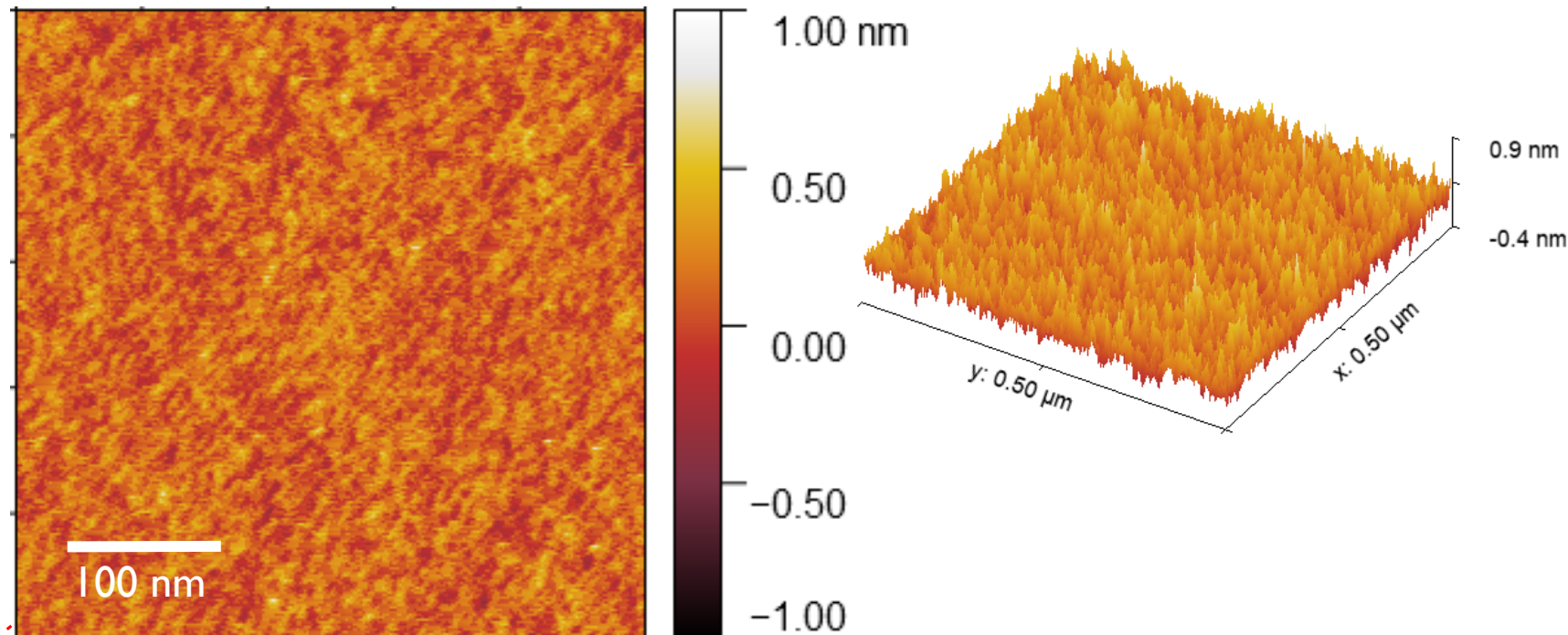
6

Chromatic Dispersion of  
CVD Oxide Layer on Si



Michael Current, Ph.D.  
Maxwell Junda, Ph.D. Covalent Metrology

## AFM Topographic Map



- Longer height variations can be seen in optical techniques over a large field of view.
- AFM looks at very small scale (atomic) height variations over a small FOV.

## Dektak Stylus Profilers

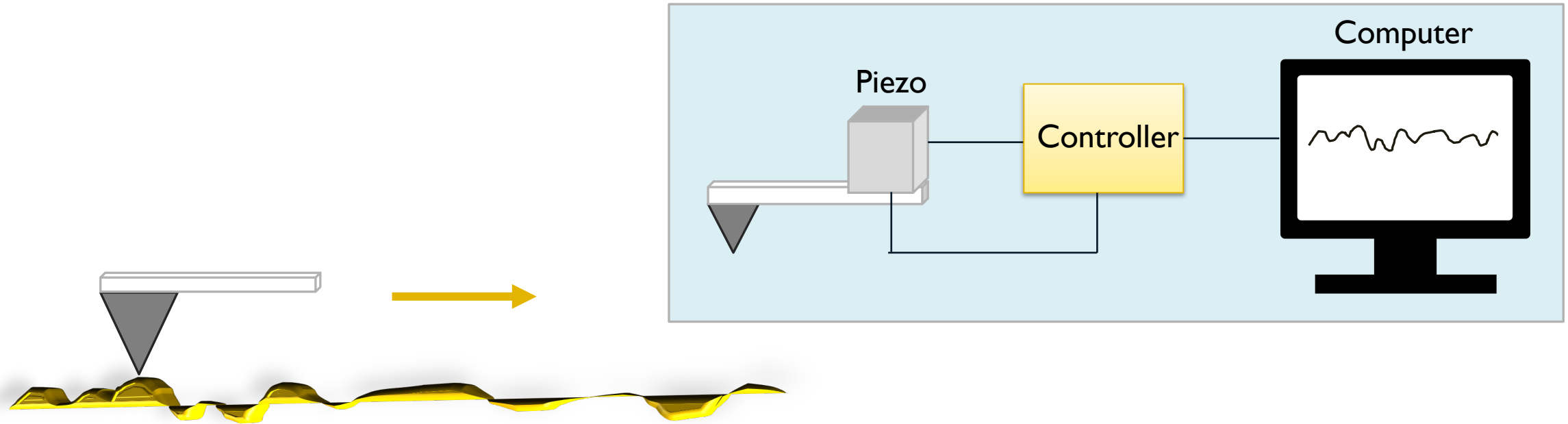
Over Four Decades of Innovation



- Stylus profilometers have been around and is probably a familiar tool.
- It's the gold standard for quick 1-D step height and roughness measurements
- Capable of mapping as a “poor man’s AFM”. Low cost option compared to AFM.



# Stylus (Line) Profilometry Overview

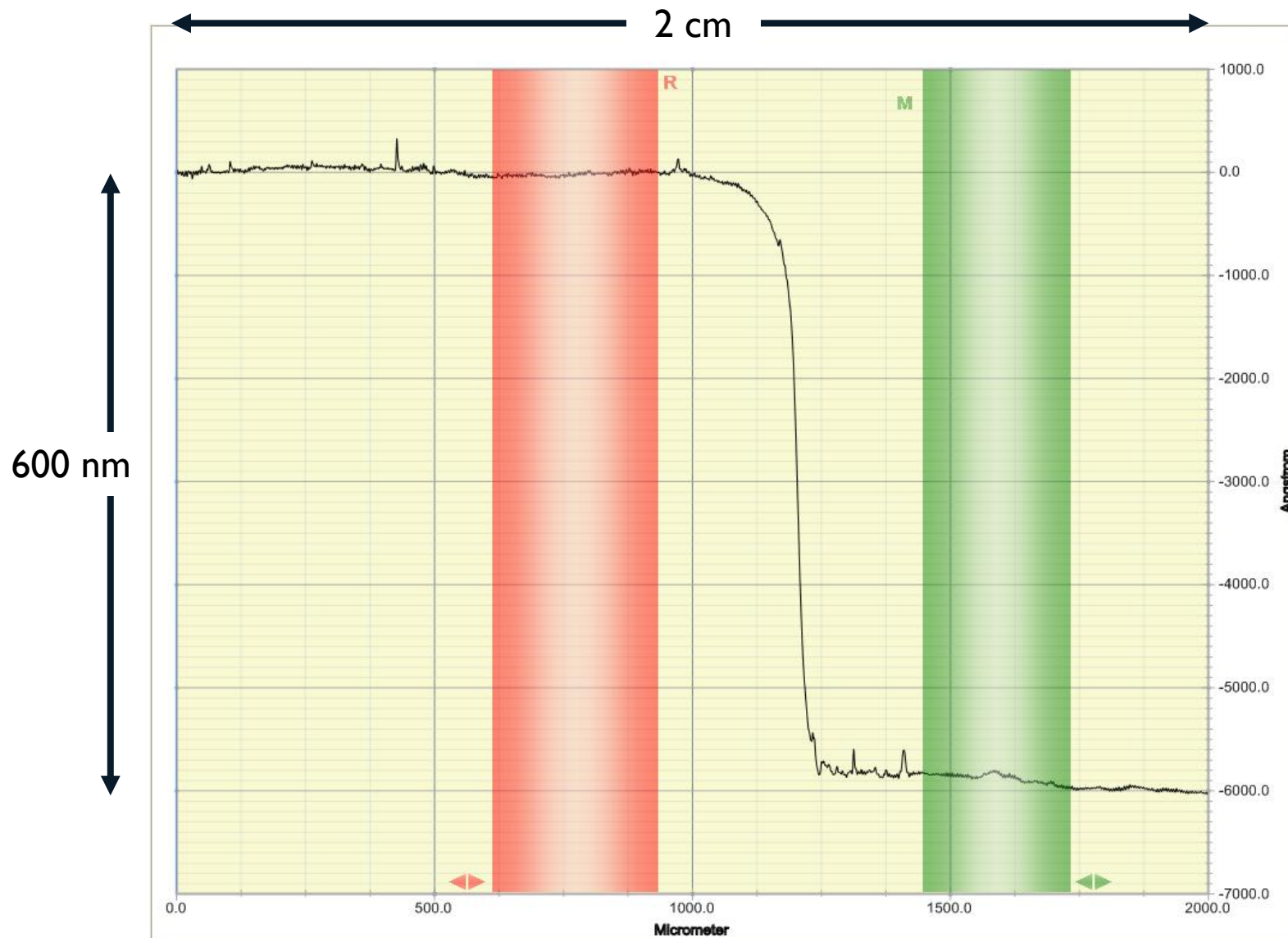


- A constant contact force is applied while the stylus moves laterally.
- The feedback controller lifts the stylus tip up or down to maintain constant force
- Tips are usually diamond. The tip radius dictates the lateral resolution.
  - Tip radius ranges from 50 nm to 200 microns

# Stylus Profilometry Excels At Long Scan Lengths and Hard Materials

## Copper Film on Silicon

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R = Reference

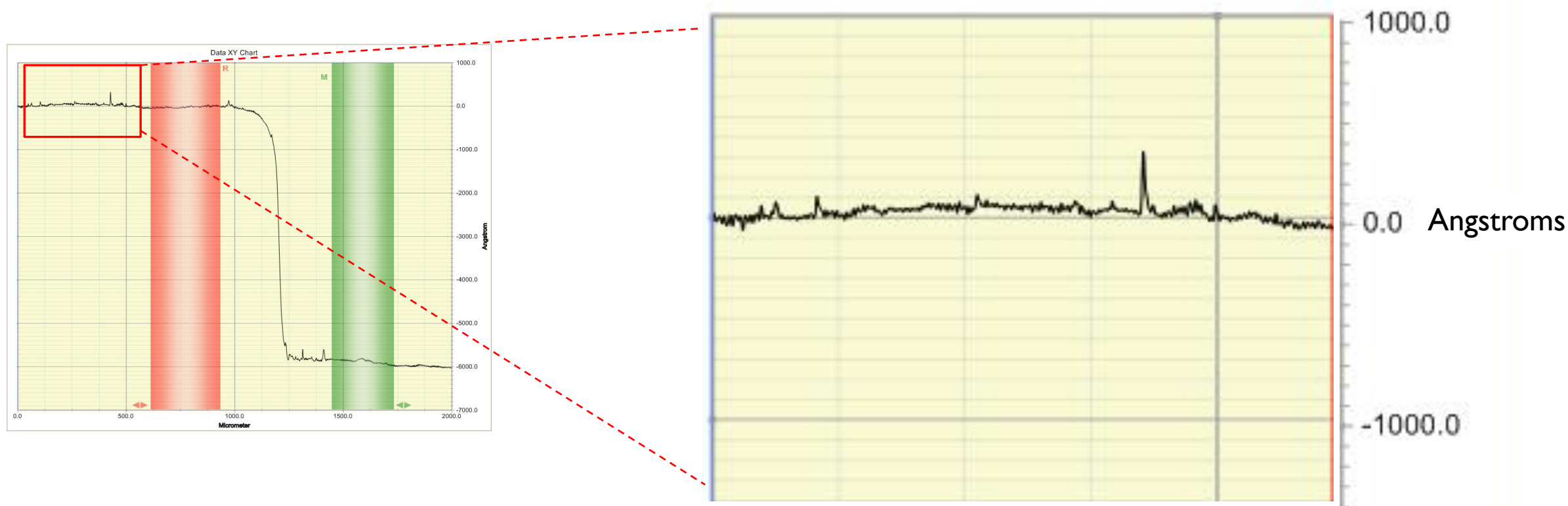
M = Measure

Height = Averaged over the  
2 regions

$$\text{Film Thickness} = R - M$$

# Stylus Profilometry for Line Roughness

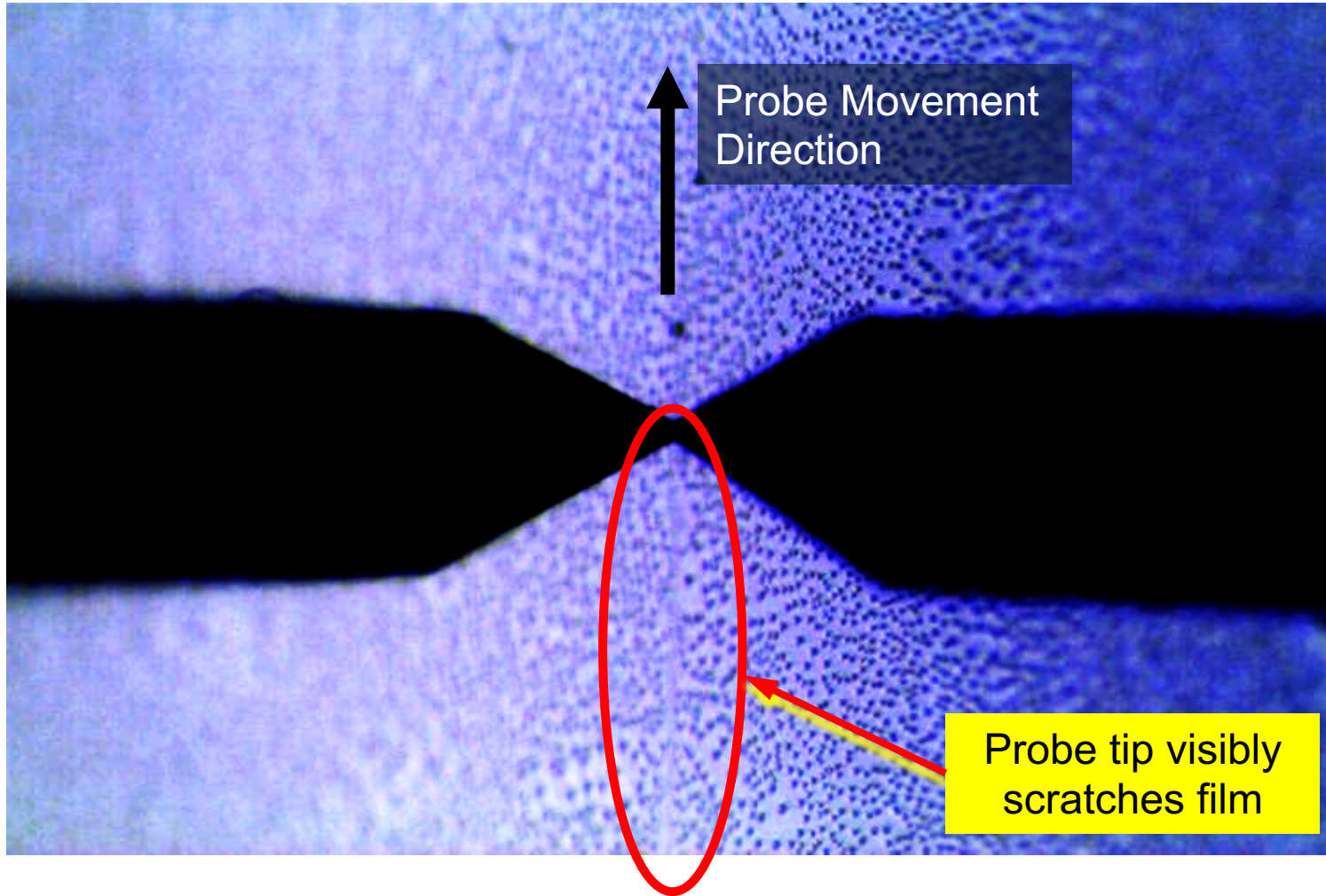
10



- Can provide a measure of line roughness. Average line roughness ~10 nm.
- Lateral and vertical resolution limitations.
  - tip dimensions, piezo vertical range (sub nanometer vertical often not achievable)

# Suffers for Soft Coatings

11

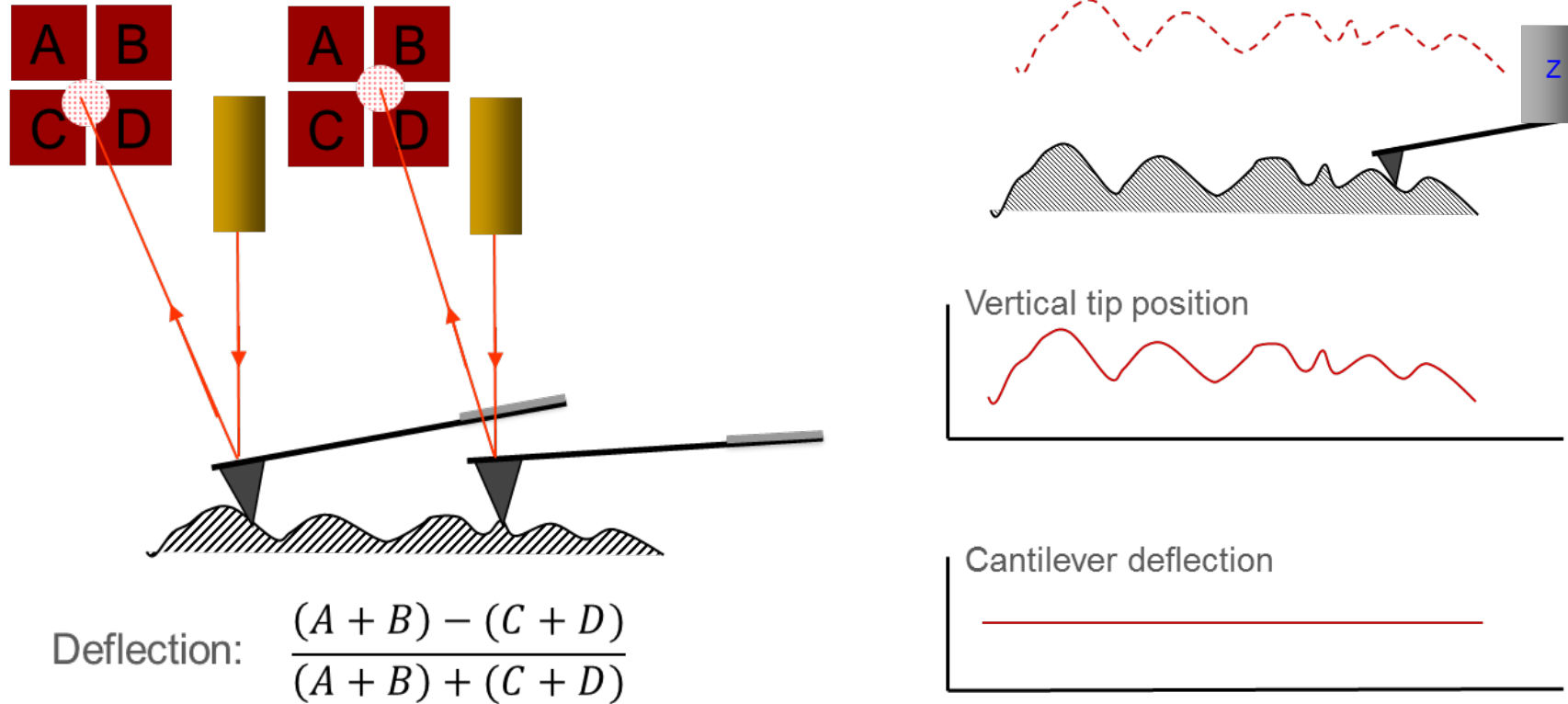




# Atomic Force Microscopy (AFM)

## 2 Methods to Measure Topography: Contact Mode

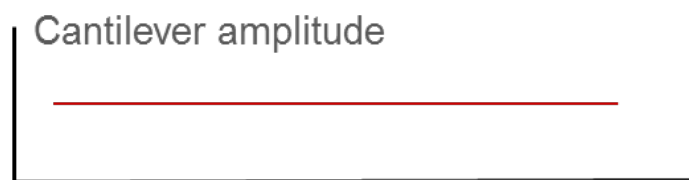
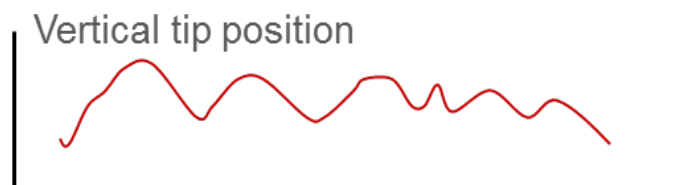
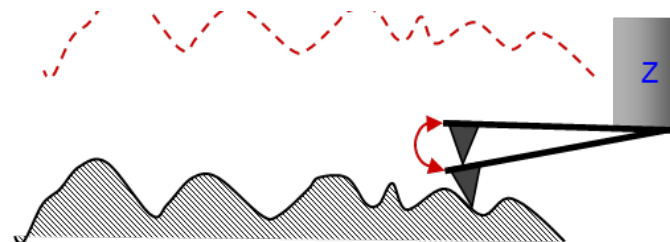
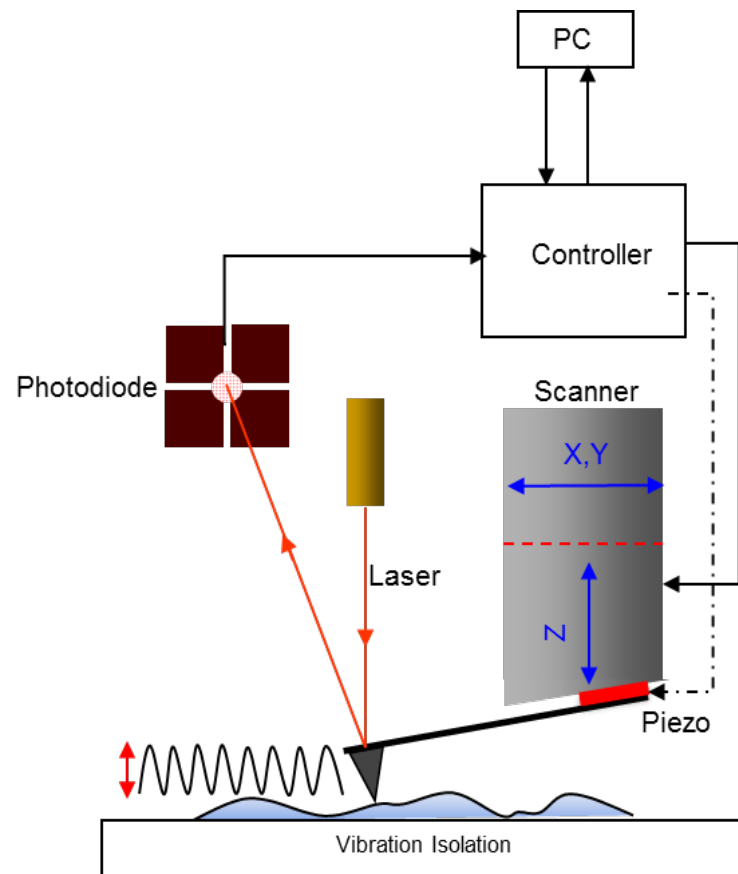
12



- Keep lever deflection constant. Tip is “dragged” across the sample
- Base for other advanced modes: conductive AFM, contact resonance, ...

# Tapping Mode (AC-Mode)

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## AFM User Controls...

- Choice of tip
- Amplitude setpoint (tip-sample distance)
- Integral gain
- Scan speed
- Scan size

- Cantilever is driven at its resonant frequency by a piezo.
- The amplitude is monitored by laser deflection.
- Constant amplitude is maintained by adjusting the z piezo up or down.

# How to Choose the Right Tip?

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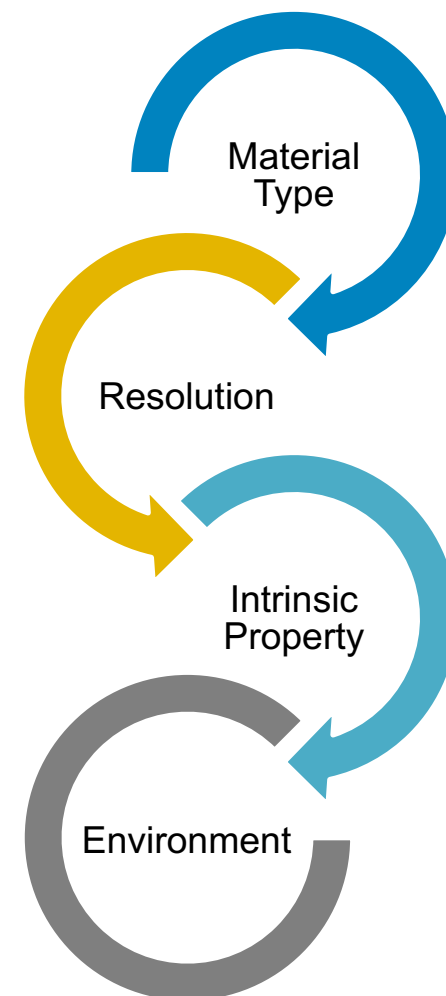
- *What's my sample/material?*
  - Is the sample hard (e.g. metals, ceramics, semiconductors) or soft (polymers, gels, biomaterials)
- *What lateral (x,y) resolution do I need?*
  - Smaller than 7-10 nm?
- *Surface properties other than topography?*
  - Mechanical (stiffness/modulus), conductivity, magnetic domain orientation, charge state,...
- *Environmental conditions?*
  - Sample needs to be imaged in liquid?

## Boils down to a few key properties:

**Spring constant (k) ... tip force**

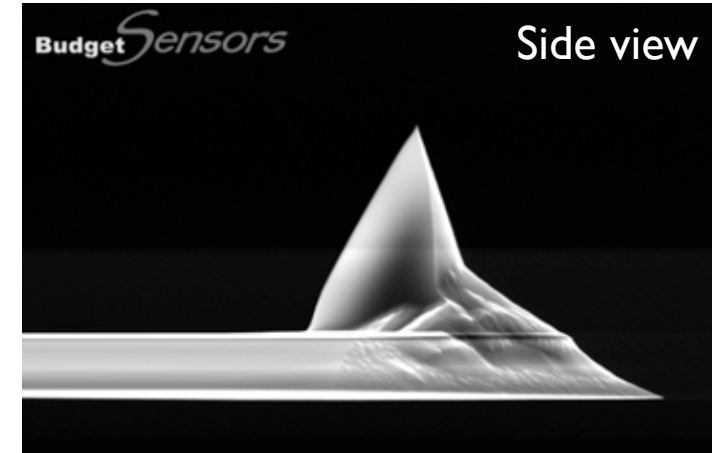
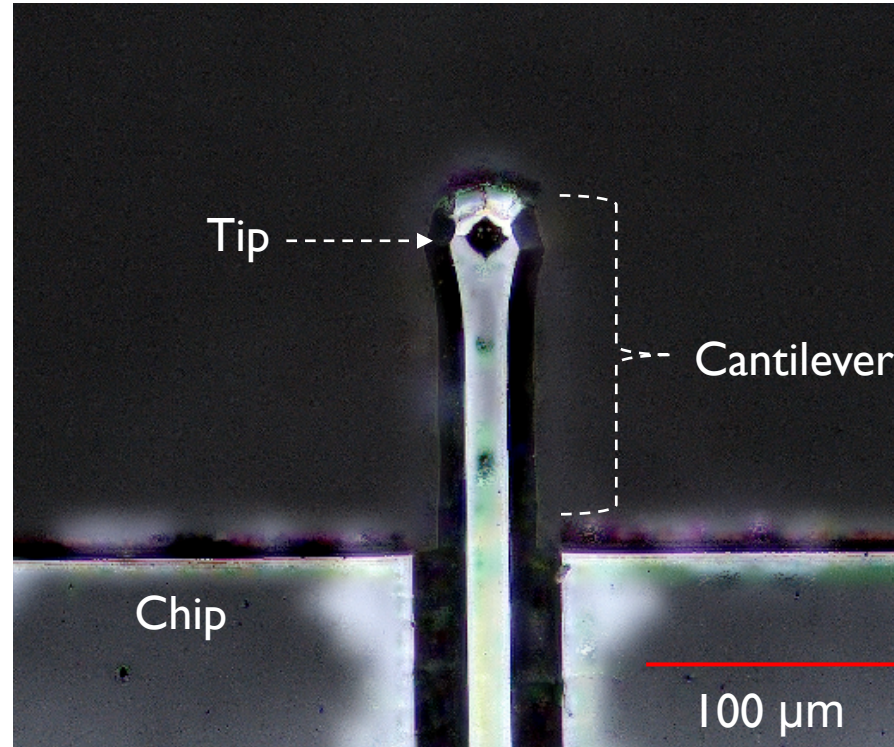
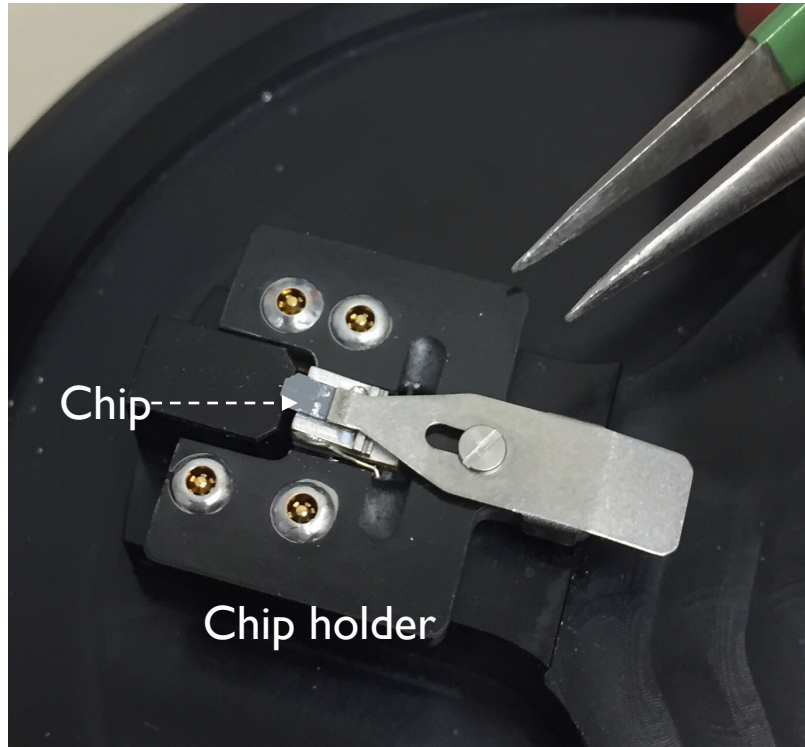
**Tip sharpness (r) ... lateral resolution**

**Resonant frequency and Q-factor ... imaging speed (will be discussed in a later webinar)**



# Anatomy of the AFM Probe

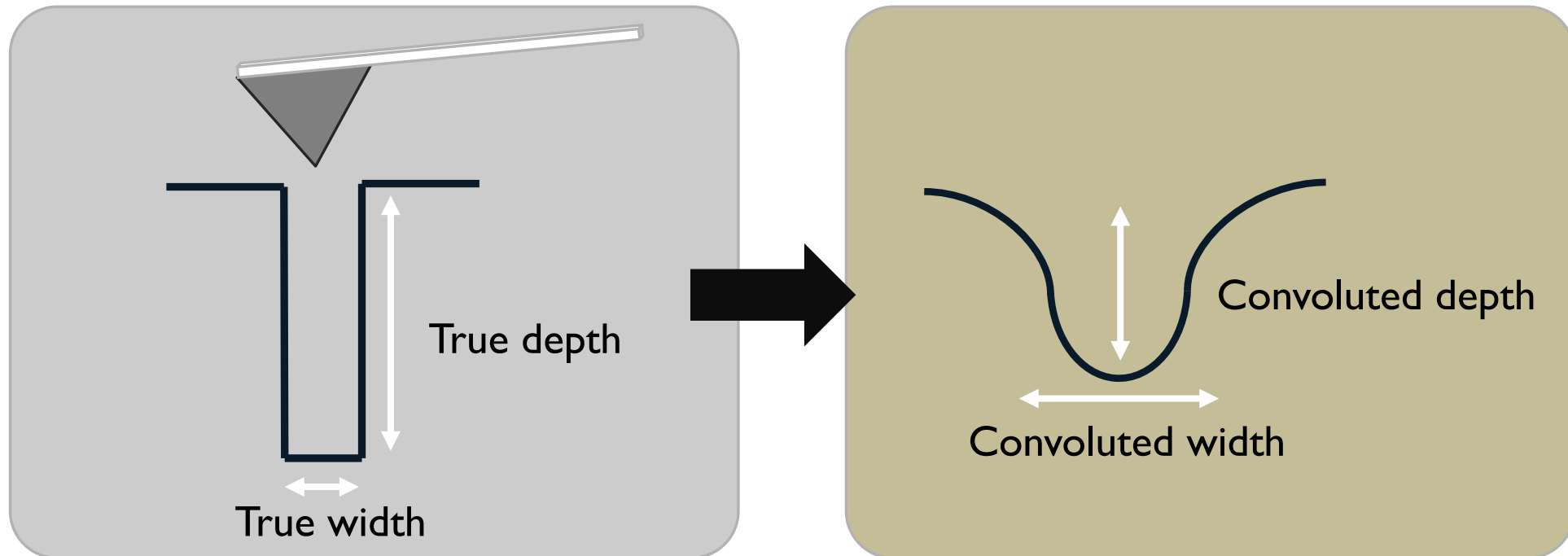
15



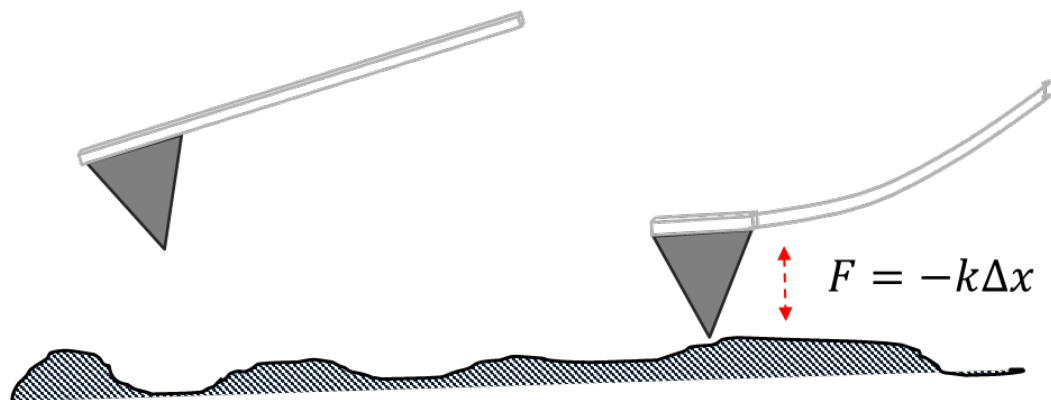
- Probes are typically made from Silicon or Silicon Nitride. Backside of cantilever usually has a reflective Al coating
- Tip radius, probe material, cantilever length can be the difference between good AFM data and bad
- **Key probe manufacturers:** NANOSENSORS, NanoWorld, BudgetSensors, MikroMasch, App Nano, NuNano.



- Radius of curvature of the tip defines the lateral resolution.
  - Not only leads to convoluted x,y dimensions, can caused convoluted depth... effects surface roughness!

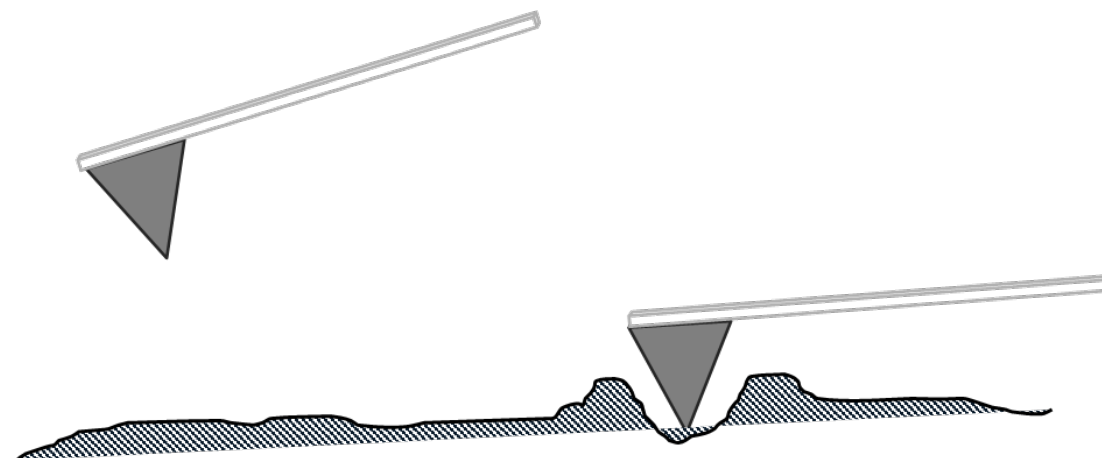


## Case 1: $K_{\text{sample}} \gg k_{\text{probe}}$



- **Think of the probe as a mass on a spring**  
 $\Delta x$  is related to the deflection or amplitude
- This case represents hard materials (ceramics, metals, semiconductors).
- Almost any choice of tip spring constant won't induce sample deformation
- Need to know if surface is sticky. Cantilever upswing is necessary for tracking

## Case 2: $K_{\text{sample}} \ll k_{\text{probe}}$

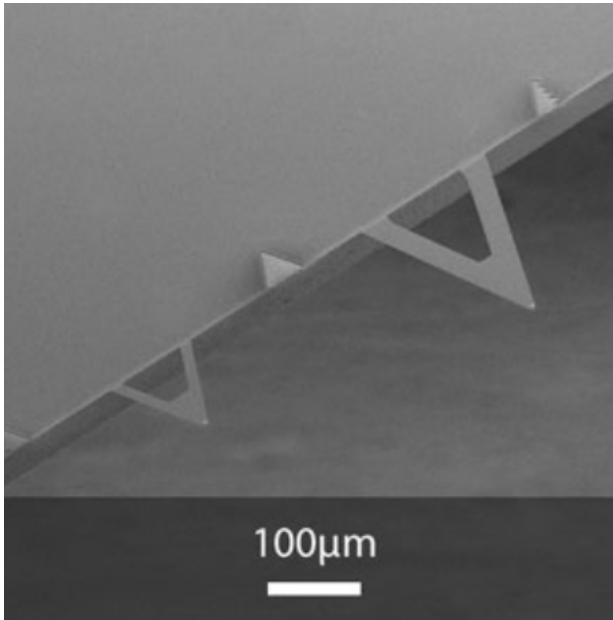


- **Tip can indent or poke through the sample**
- This case represents soft materials (polymers, gels, membranes)
- Require a tip in which  $k_{\text{probe}}$  is less than or comparable to  $K_{\text{sample}}$

# AFM Probes Have Evolved Into a Variety of Species

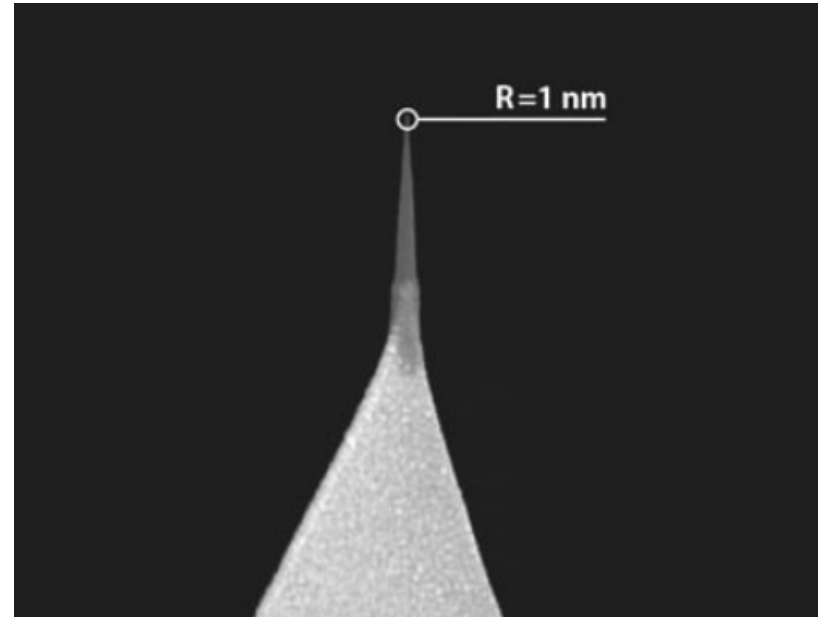
18

XNC12/Cr-Au by



Soft cantilevers, low frequency  
Imaging in liquid, soft materials

SHR150 by Budget Sensors



Super sharp tip  
High lateral resolution

EBD-NCH by Nanotools

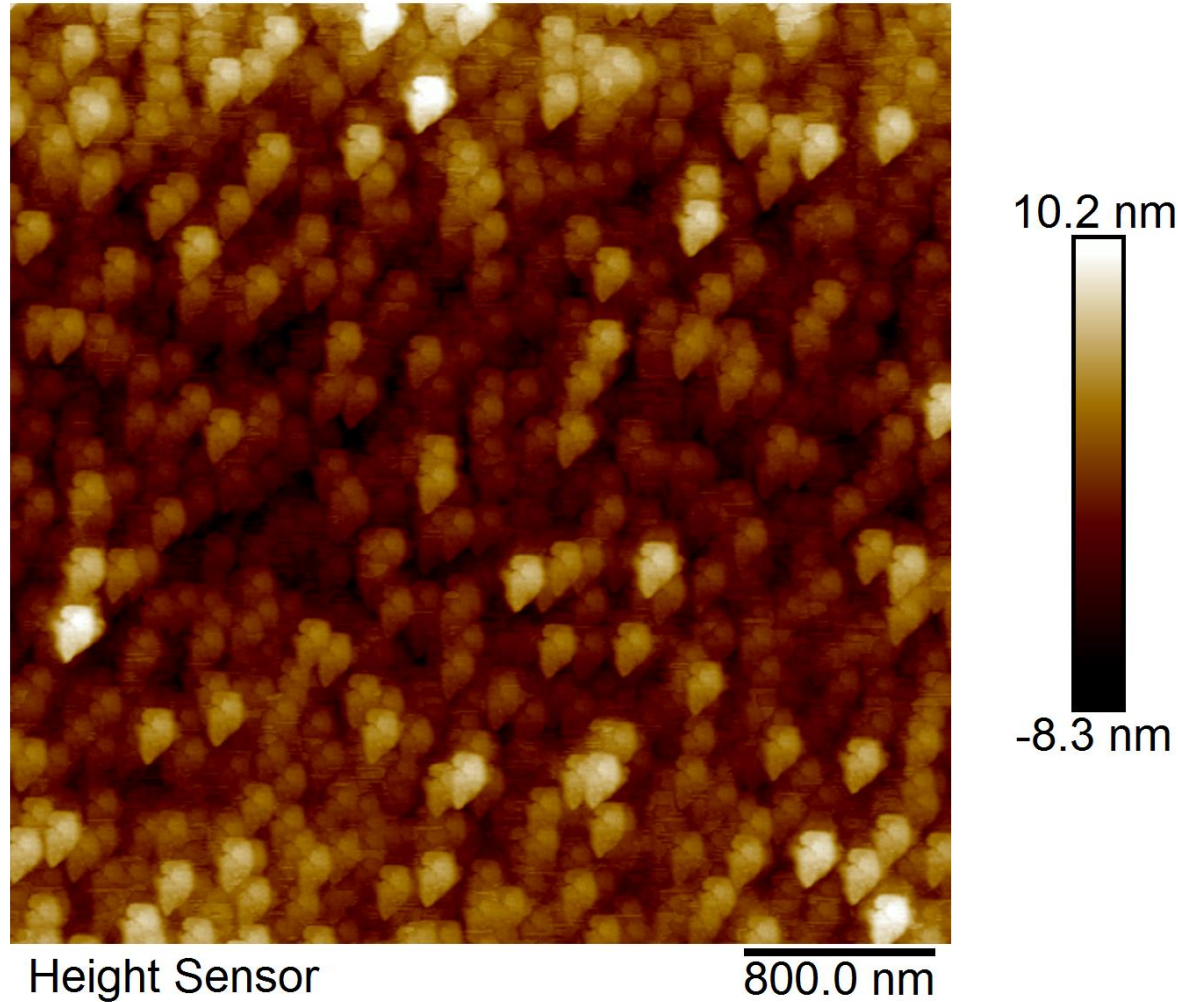


Diamond-like electron beam  
deposited (EBD)  
Cone shaped, hard contact, wear  
resistant

# Tip Wear and Tip Contamination

19

- Don't bother cleaning or sharpening tips. They are consumables.





# Tip-Check Samples

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## Wear-resistant coating on silicon

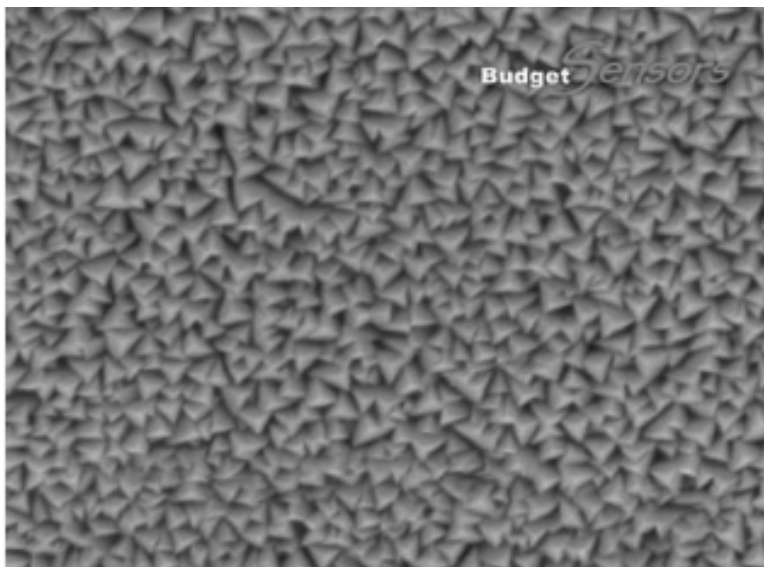
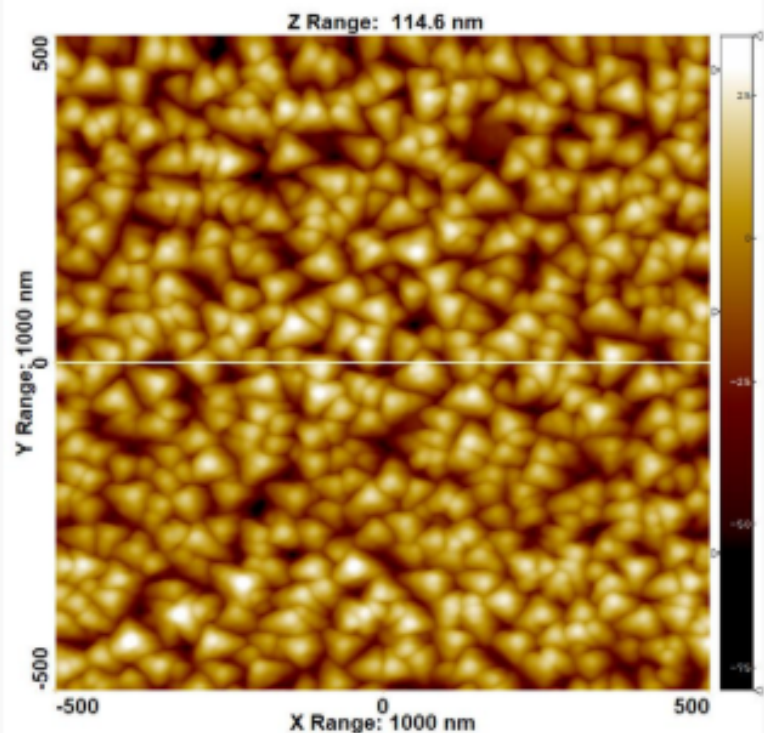


Image Courtesy BudgetSensors and NanoAndMore

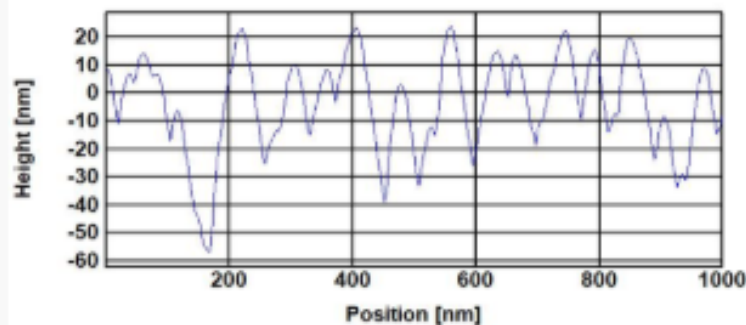
Differences in peak to valley (Rz) roughness can be seen

### Sharp Tip

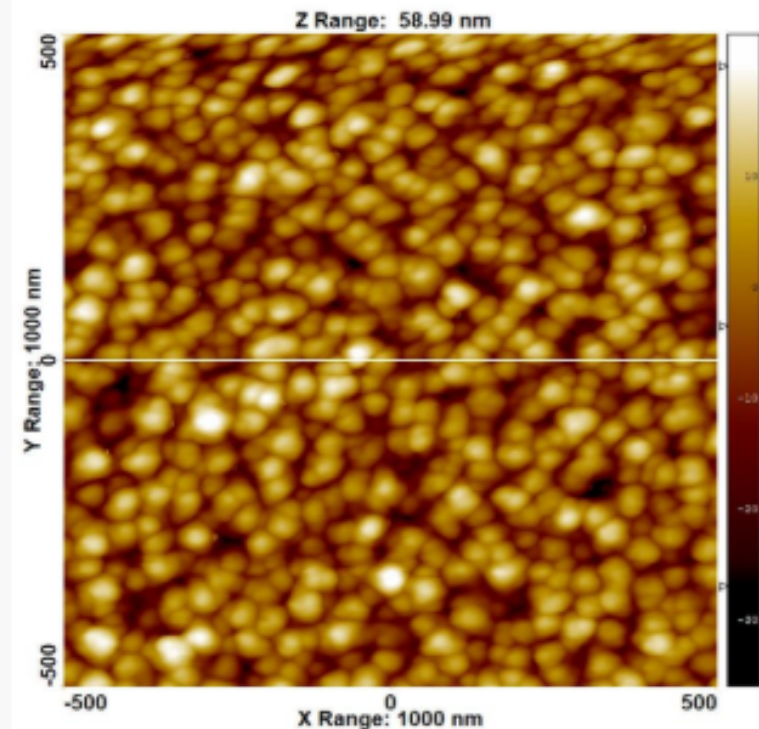


Line No: 256

**Rz = 80 nm**

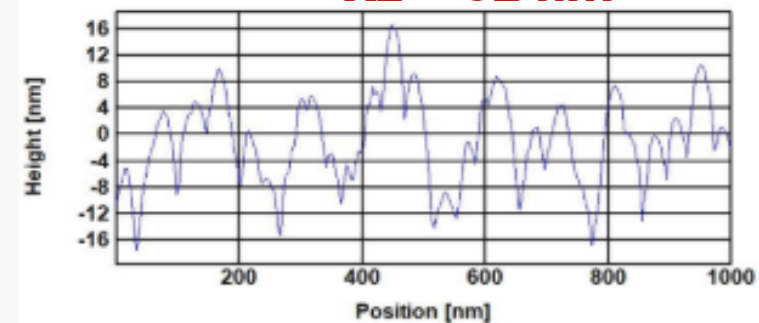


### Worn tip

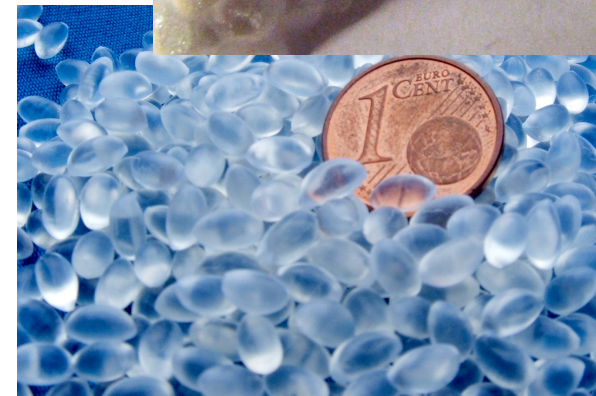


Line No: 256

**Rz = 32 nm**

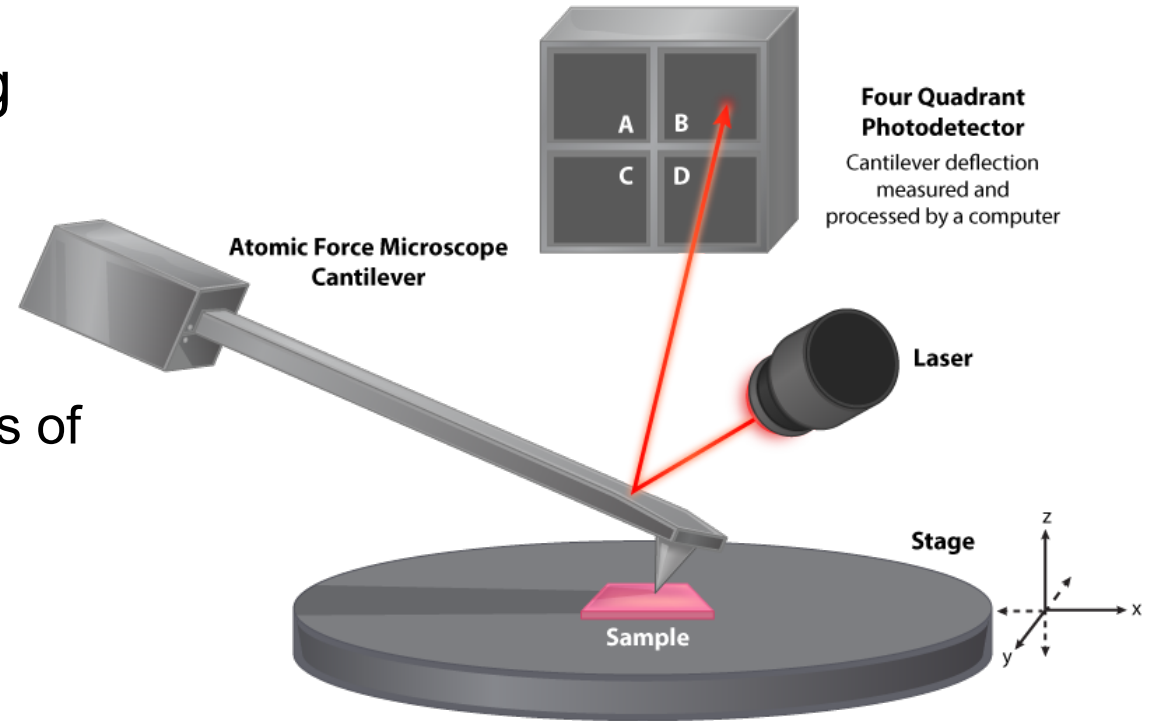


- Does your sample or surface change under ambient conditions?
  - Ambient conditions fluctuate seasonally
  - Hygroscopic samples? e.g. in some cases polymers, salts, powders, woody biomass
- AFMs can be operated under controlled temperature and humidity





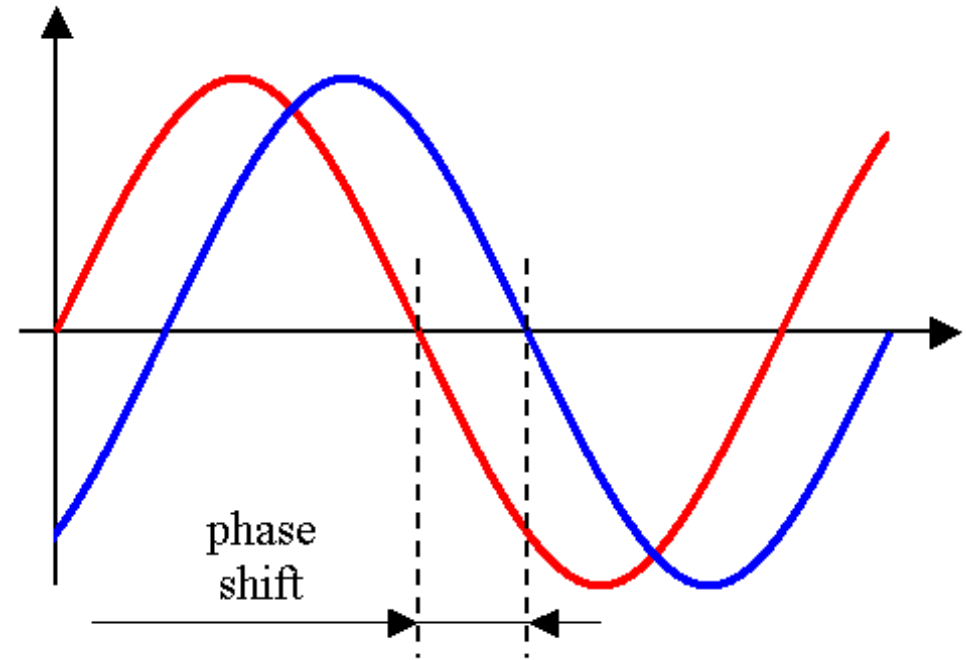
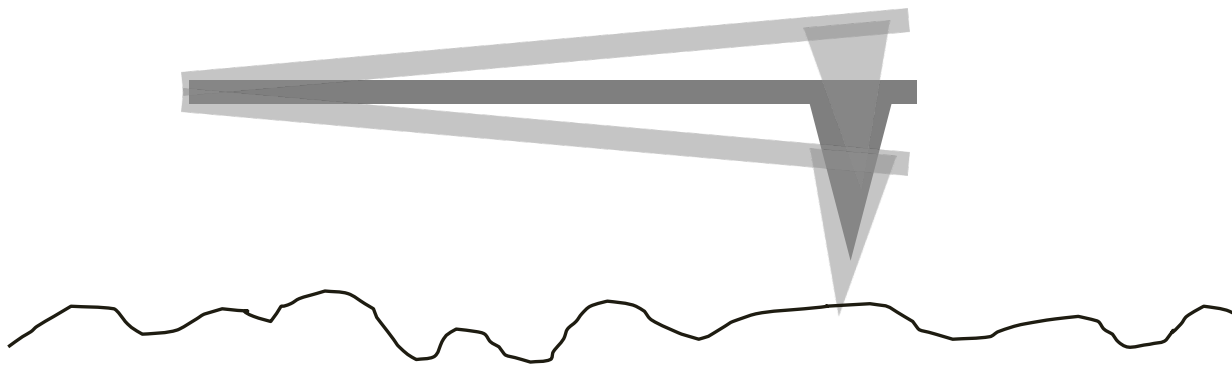
- Sample needs to sit still during scanning
- ✓ Flat and flush on the stage
- ✓ Magnets work great for mounting sample
- ✓ Epoxy also works wells for thin or brittle sheets of material to mount on a glass slide.
- ✗ Tape tends to cause drift during the scan



# Engaging the Tip on the Sample: Optimizing Sensitivity while Maintaining Tracking

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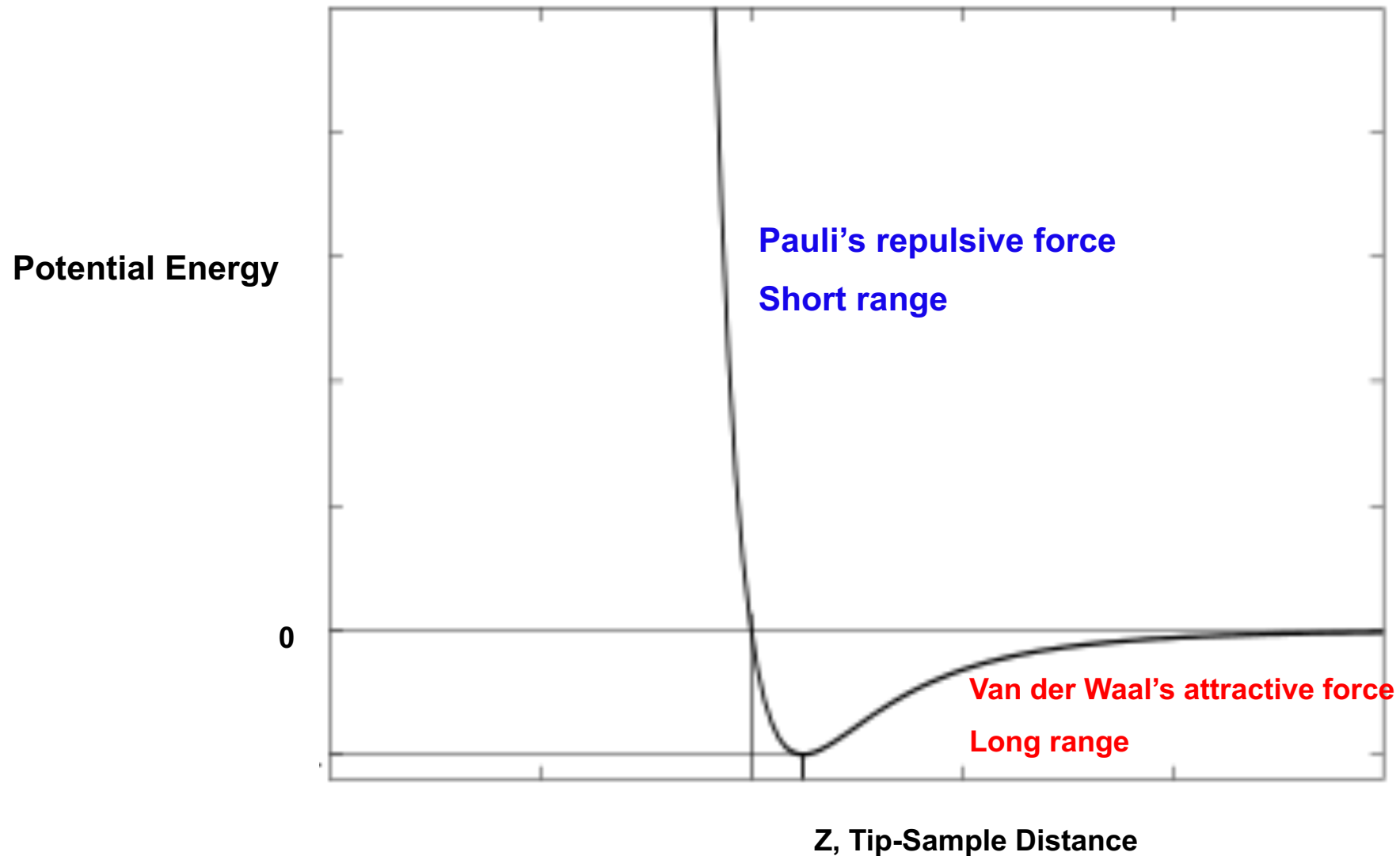
- Monitor the change in amplitude and phase signal
- Choice of setpoint amplitude (engaged) relative to free air (not engaged) amplitude
  - Is your sample soft? Eliminate tip-induced damage, or false height readings.
- Integral gain and scan speed

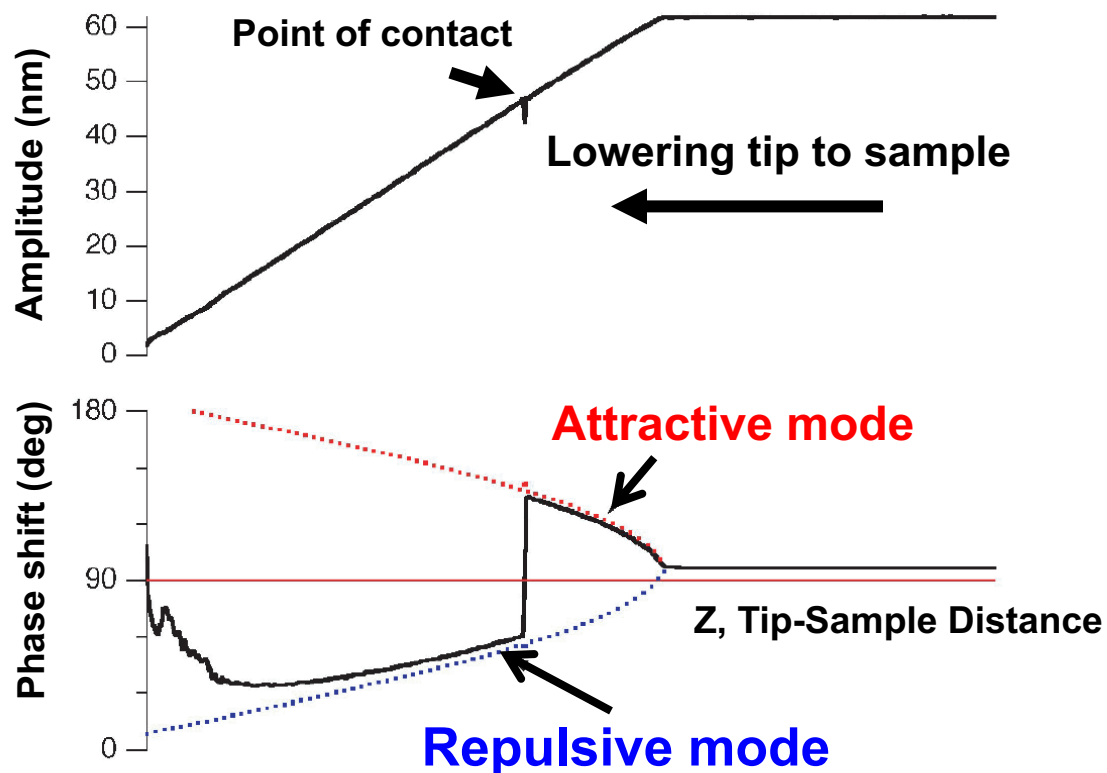


- Phase shifts is the deviation of the output signal from the drive signal.
- Phase shifts can be caused by sharp changes in height and/or differences in material compliance
- Positive/negative shifts are caused by differences in tip-sample force...



## Lennard-Jones Potential





In **attractive mode**, the tip turns around before contacting surface, while in **repulsive mode**, it makes intermittent contact with surface.

**Attractive mode** much less invasive (favorable for soft samples)

**Phase 90-180deg: Long-range attractive forces dominate tip-sample interaction (attractive mode)**

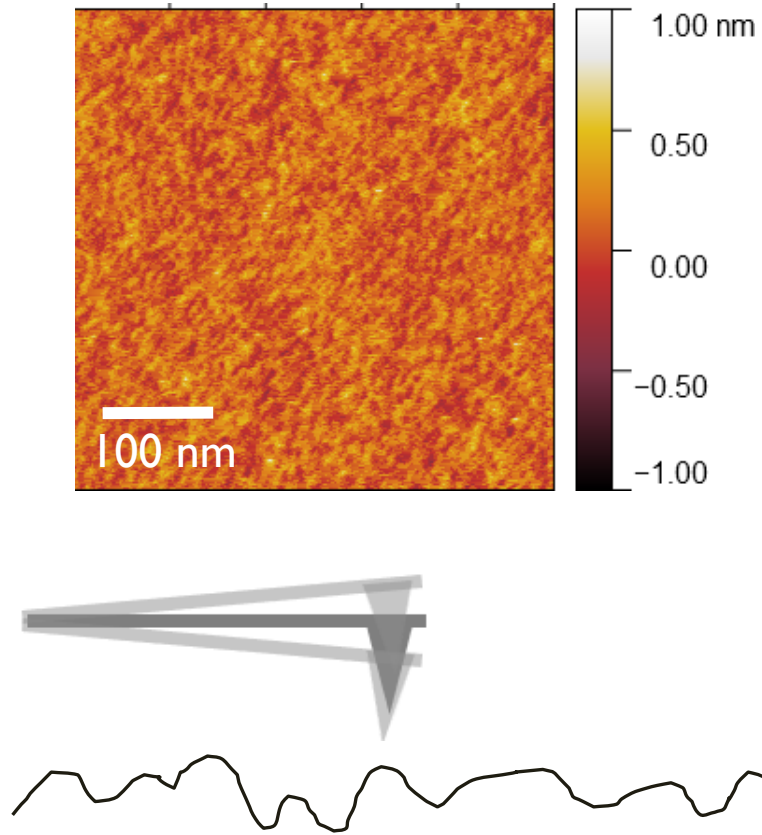
**Phase 0-90deg: Short range repulsive forces dominate (repulsive mode)**

# CVD Oxide Film on Silicon Wafer

## Comparison of Attractive and Repulsive Imaging Modes

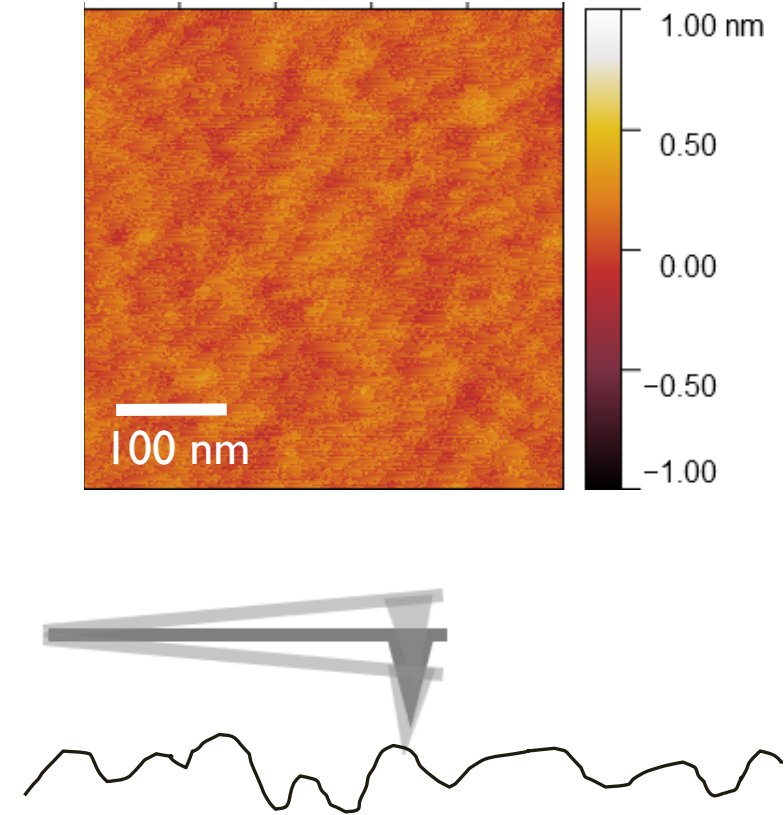
27

**Attractive mode**



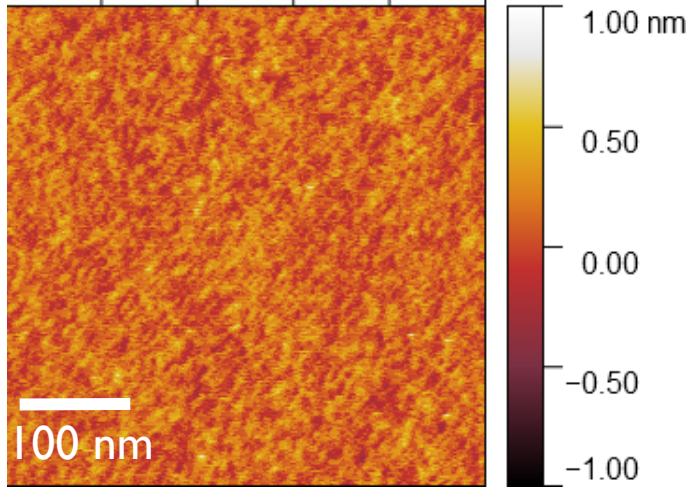
Dominant tip force is attractive  
Gentle, "non-contact"

**Repulsive mode**



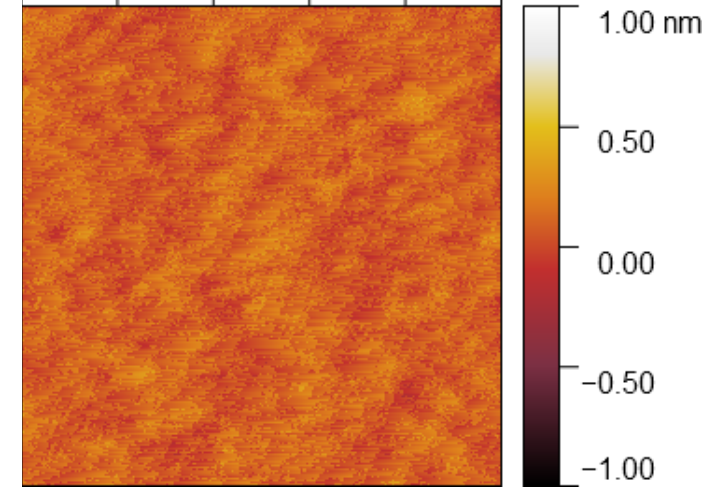
Dominant tip force is repulsive  
Tip is hammering at surface

**Attractive mode**



Sq = 0.145 nm

**Repulsive mode**



Sq = 0.086 nm

0.06 nm difference in RMS surface roughness significant?

*Yes, if noise floor (~0.01 nm) is only variable.*

*Variability in tip, sample, mechanical/electrical noise, etc.*

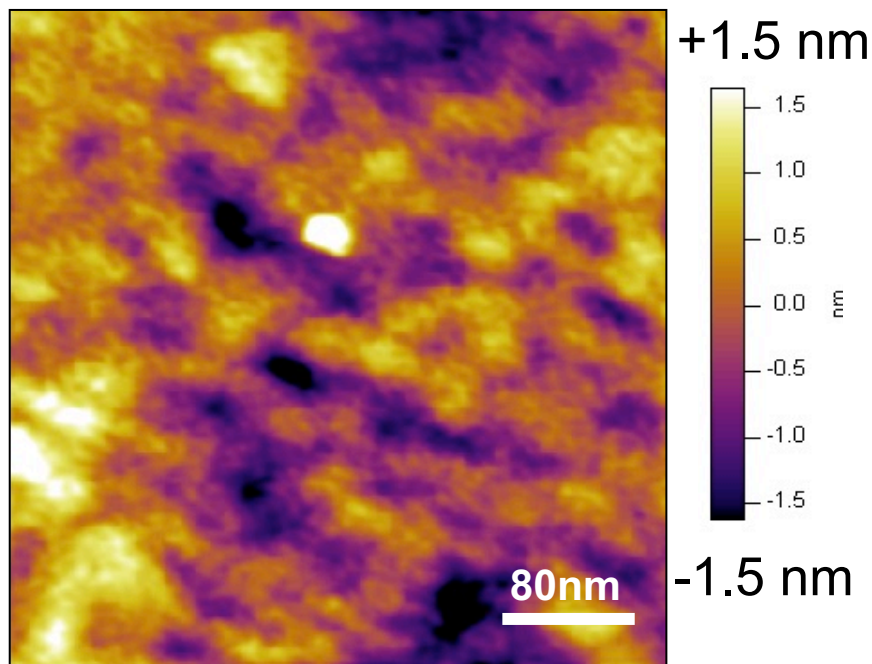
Sub-angstrom resolution relevant to your materials/process?



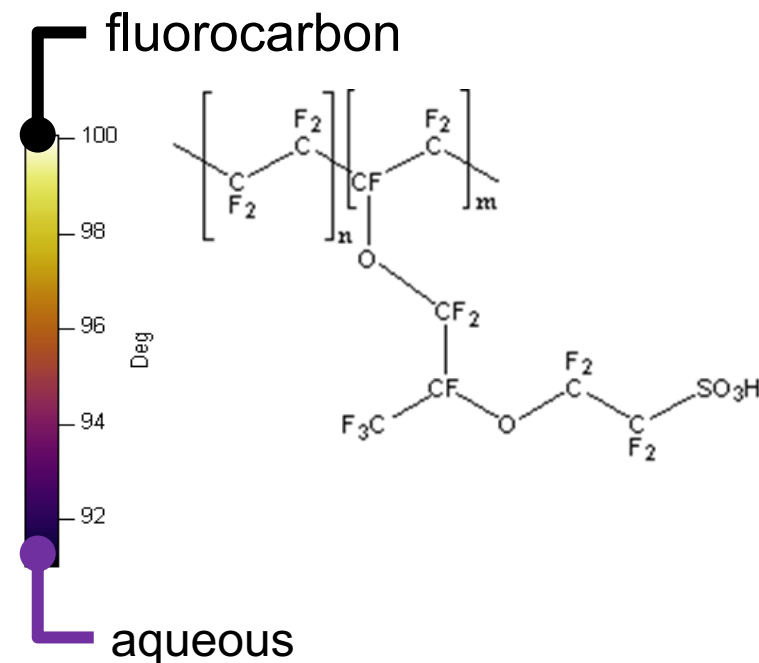
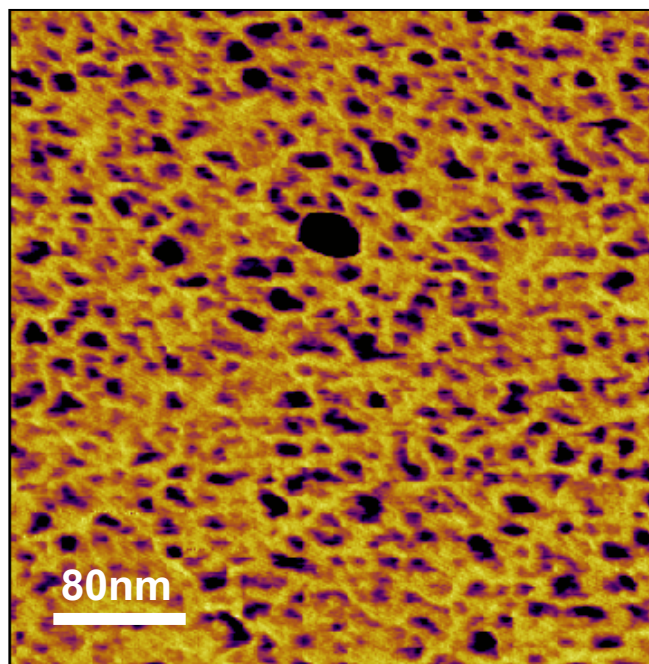
# Phase Imaging for Nanomechanical Characterization Proton Exchange Membranes

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## Height



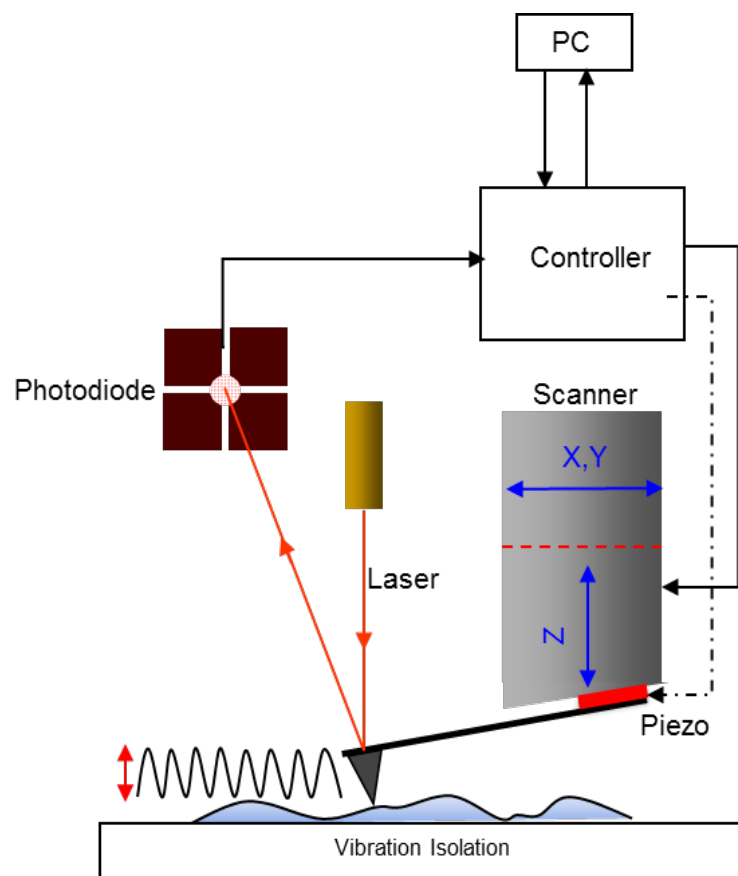
## Phase



- Sometimes the topography is not meaningful
- Phase contrast is related to chemical heterogeneity to the surface

19.4% hydrophilic  
Average domain size = 94 nm<sup>2</sup>  
10.9 nm diameter

# Choice of Integral Gain and Scan Speed to Improve Surface Tracking



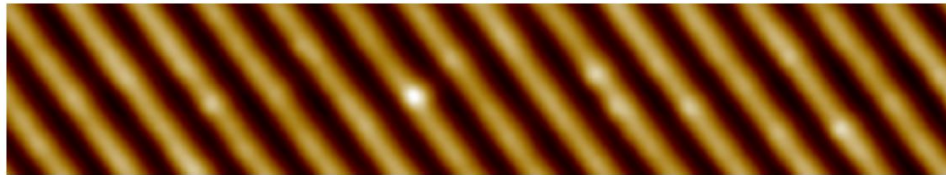
- Gain is related to the controller – controls speed of feedback
  - Integral gain is the integrated error over time
- **Low Gain:** Never reach setpoint amplitude. False height readings.
- **High Gain:** Ringing in trace and retrace scans. Adds noise
- **Scan speed:** 1 Hz scan rate typical. Can lose tracking from surface, tip can parachute off a large feature if too fast.

# Calibration Grating

## Effect of Integral Gain and Scan Speed on Surface Tracking

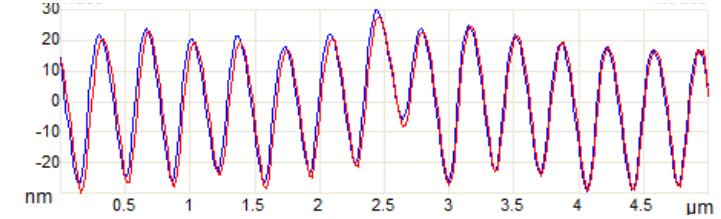
31

**Clean Scan**

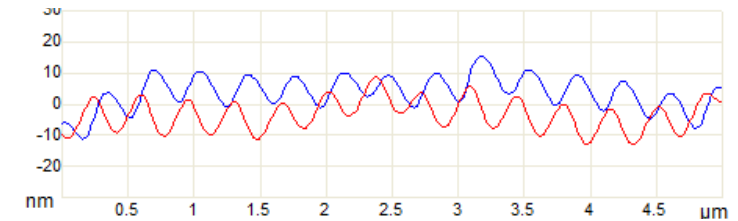
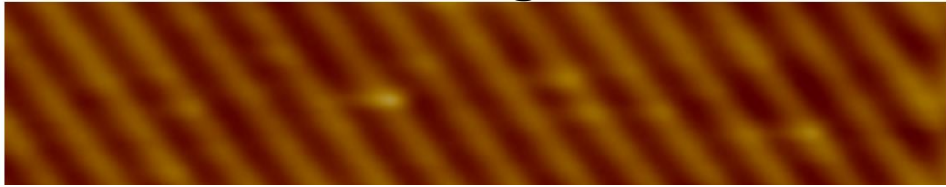


20.0 nm  
-20.0 nm

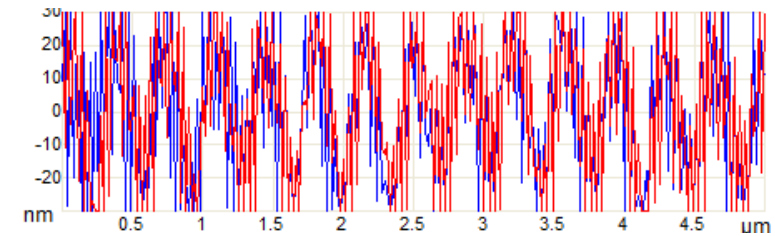
Trace -->      <--- Retrace



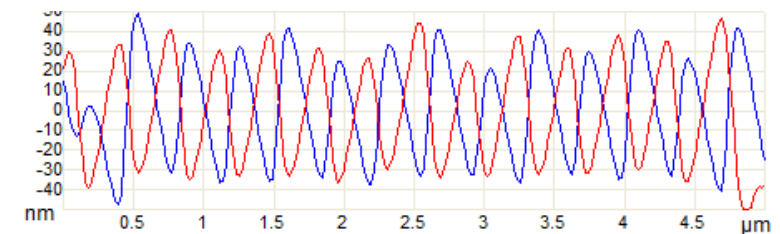
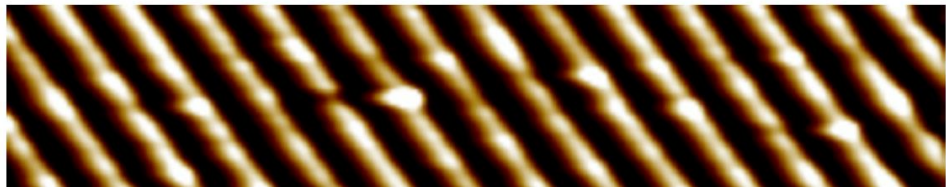
**Low Integral Gain**



**High Integral Gain**



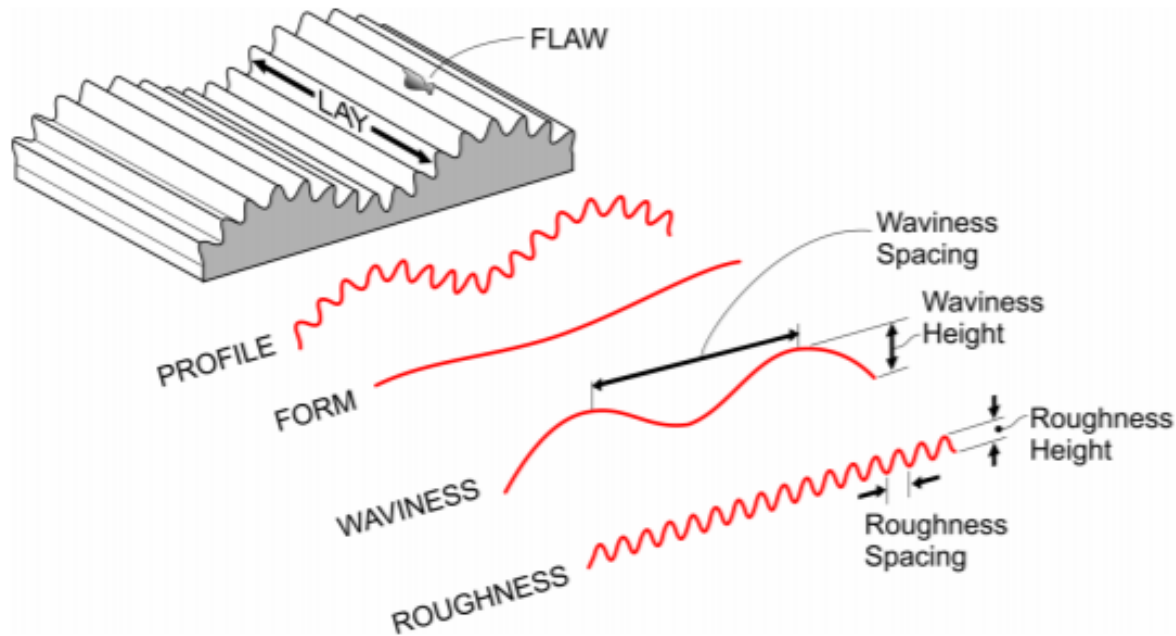
**High Scan Speed**



# What Scan Size Do I Choose for Surface Roughness?

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## Zygo Mx Surface Texture Parameters



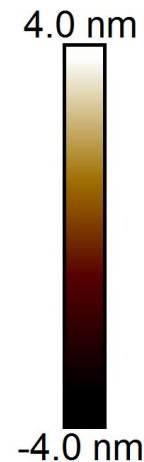
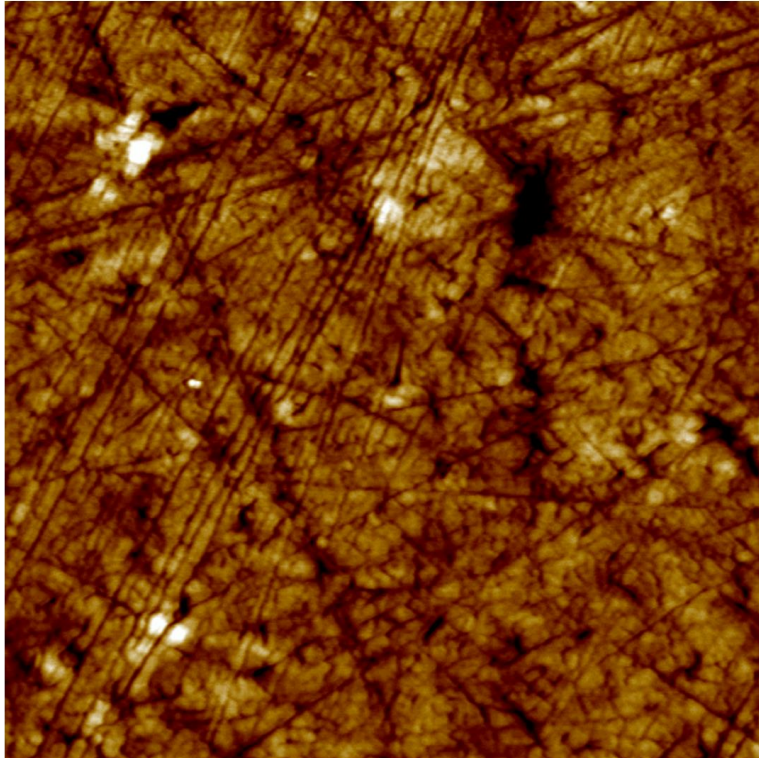
- Roughness depends on frequency
  - lowest frequency = size of the image, highest frequency = pixel size.
- Pixel resolution typically fixed (512 pixels/line)
  - Oversampling if pixel size is less than tip radius
- *Could you take a maximum scan size image with a pixel size 10 nm?*
  - Yes, but the scan would take an eternity.
- Better alternative is to take an image at a small scan size (2x2 micron) and a larger scan size (10x10 micron)



# Topography of Steel 304: Surface Roughness on Different Length Scales

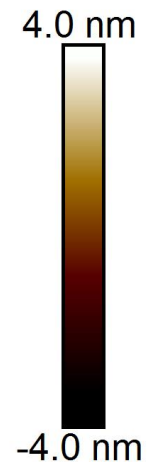
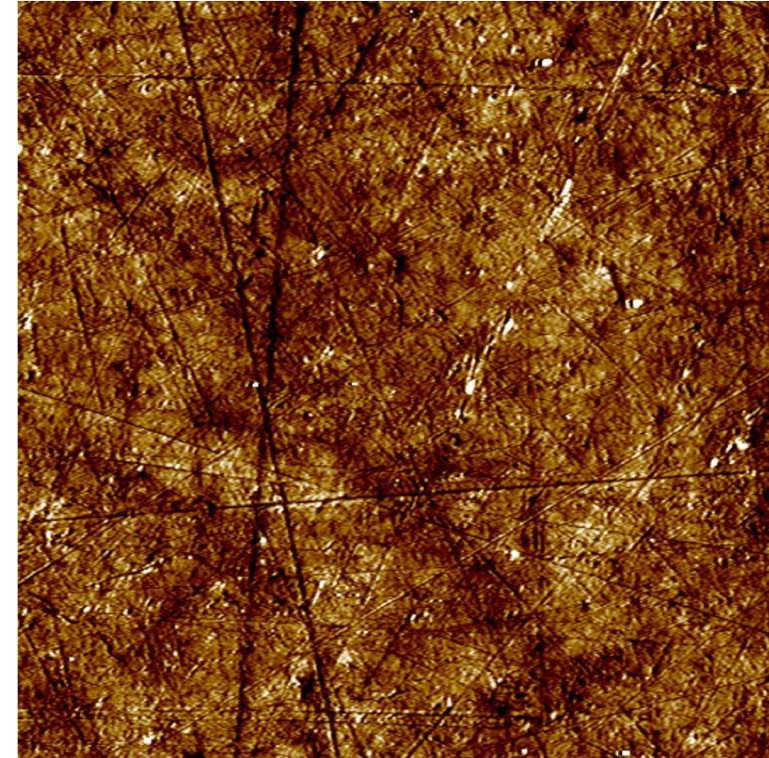
33

2  $\mu\text{m}$  x 2  $\mu\text{m}$



Avg. Surface Roughness  $S_a = 0.70$  nm  
RMS Surface Roughness  $S_q = 0.97$  nm  
Peak-Valley Surface Roughness  $S_z = 20.41$  nm

10  $\mu\text{m}$  x 10  $\mu\text{m}$



$S_a = 0.94$  nm  
 $S_q = 1.28$  nm  
 $S_z = 53.03$  nm

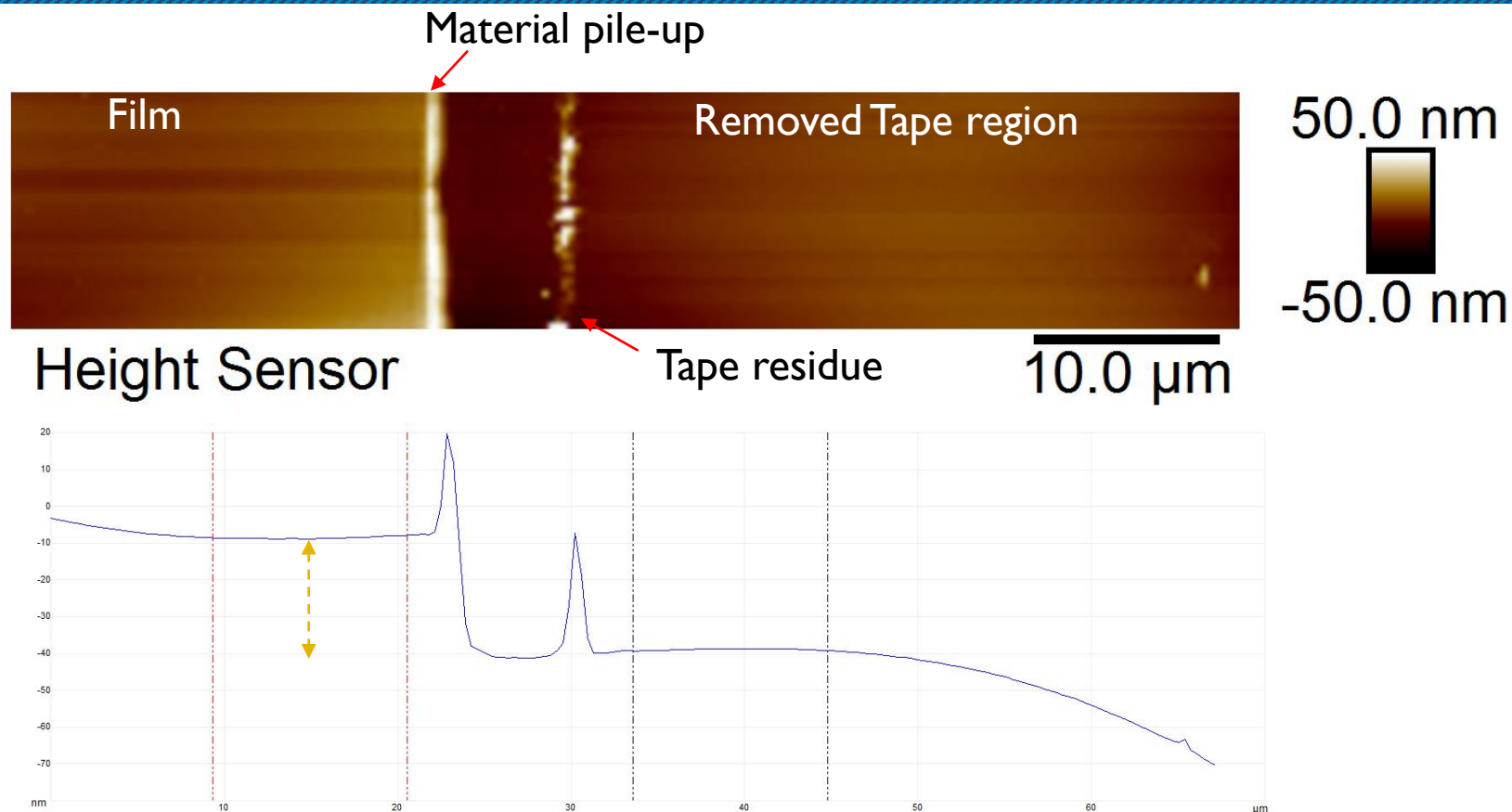
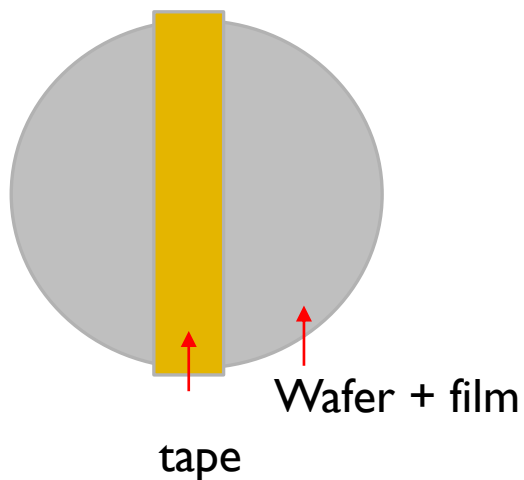
*Which set of roughness parameters represents the surface?*

- Material/Intrinsic length scales relevant to you
- Larger FOV ->  $S_z$ , waviness, but sacrificing resolution



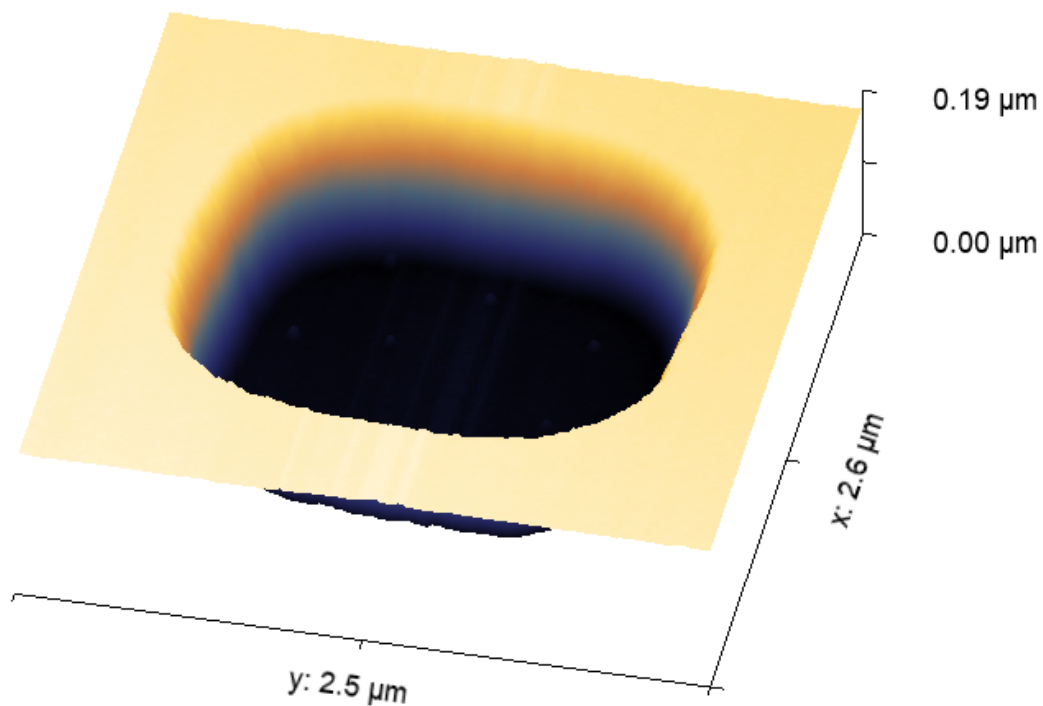
# Bow Artifacts Over Large Scan Lengths

34

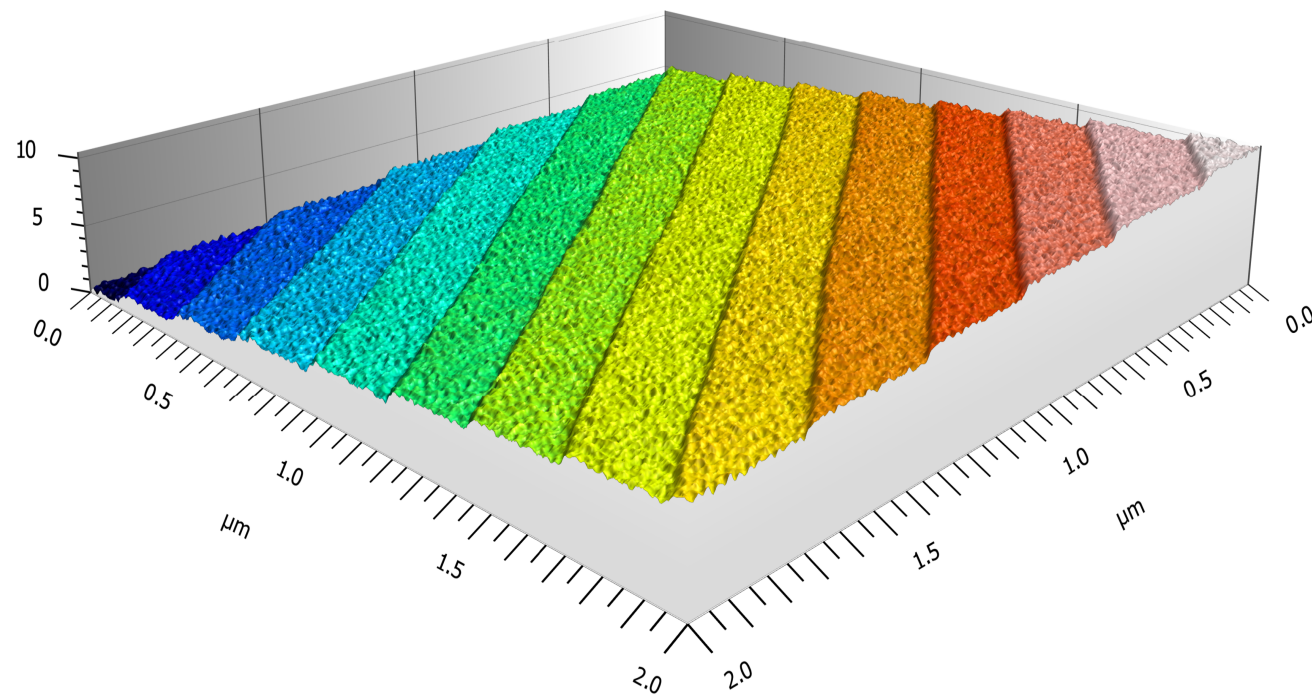


- Bow artifacts are caused by the non-linearity of the piezo extension over large lengths
- This artifact is common with XYZ scanner tubes.
  - Sometimes this can be corrected with flattening or plane-fitting.
  - XY scanners decoupled from the z scanner can mitigate the artifact

VLSI Standard Piezo Calibration sample



SiC sample collected on new Anton Paar Tosca 400



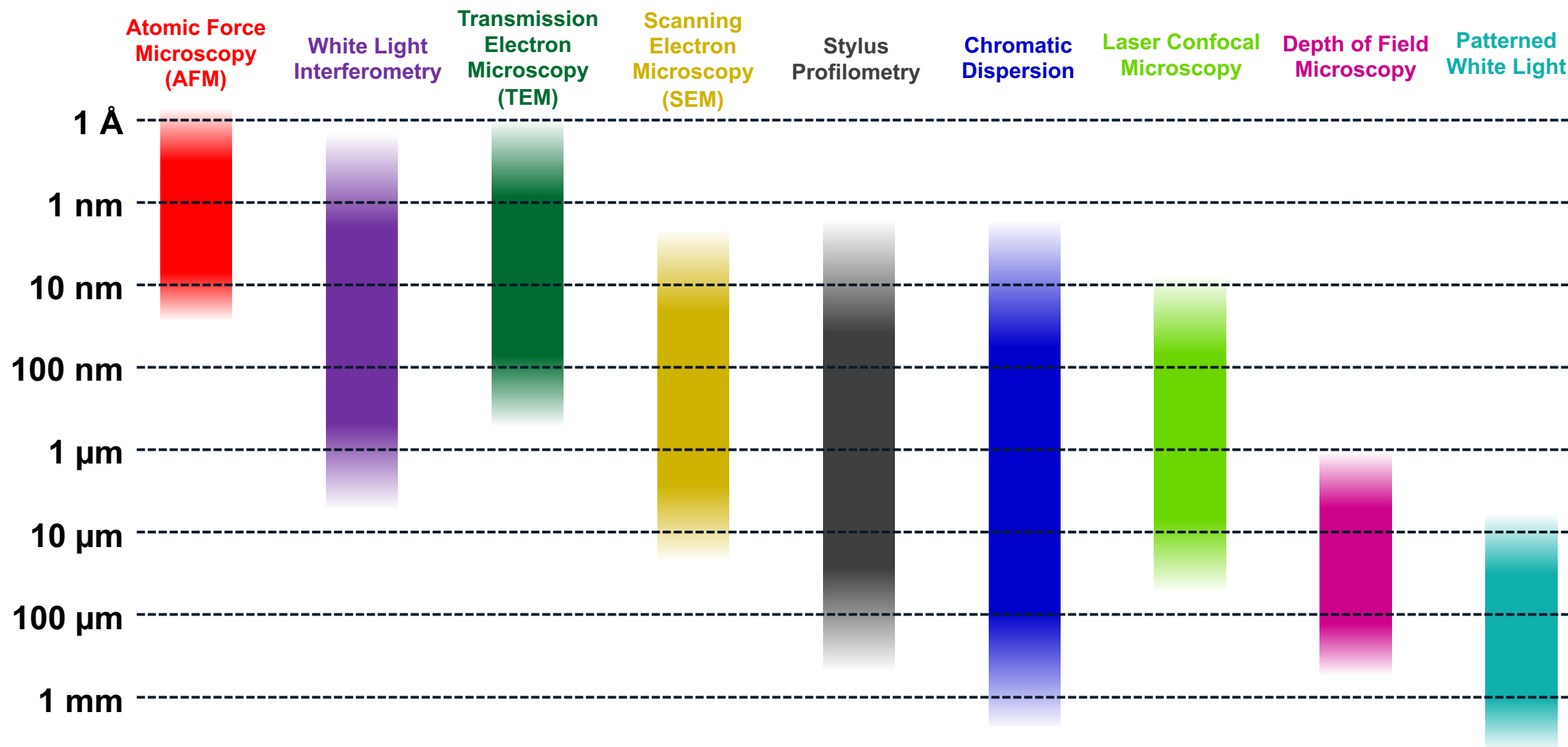
- X,Y, Z calibration can be achieved with a VLSI standard.
- Sub nm step heights (0.75 nm) can be calibrated against SiC samples.

- **Bruker** – Leading manufacturer (acquired Veeco 10 years ago). Bruker Icon in-house at Covalent.
- **Park Systems** – Est. in the 90s as Park Scientific, dominant in industry.
- **Asylum Research** - Owned by Oxford Instruments, major player in academia.
- **Anton Paar** – new to AFM market, Tosca 400 AFM soon to be in-house at Covalent.
- All provide top of the line AFMs to handle large samples as well as offering low cost AFMs.

# Summary of 3 Part Series

## Roughness Scale (Vertical Range)

37

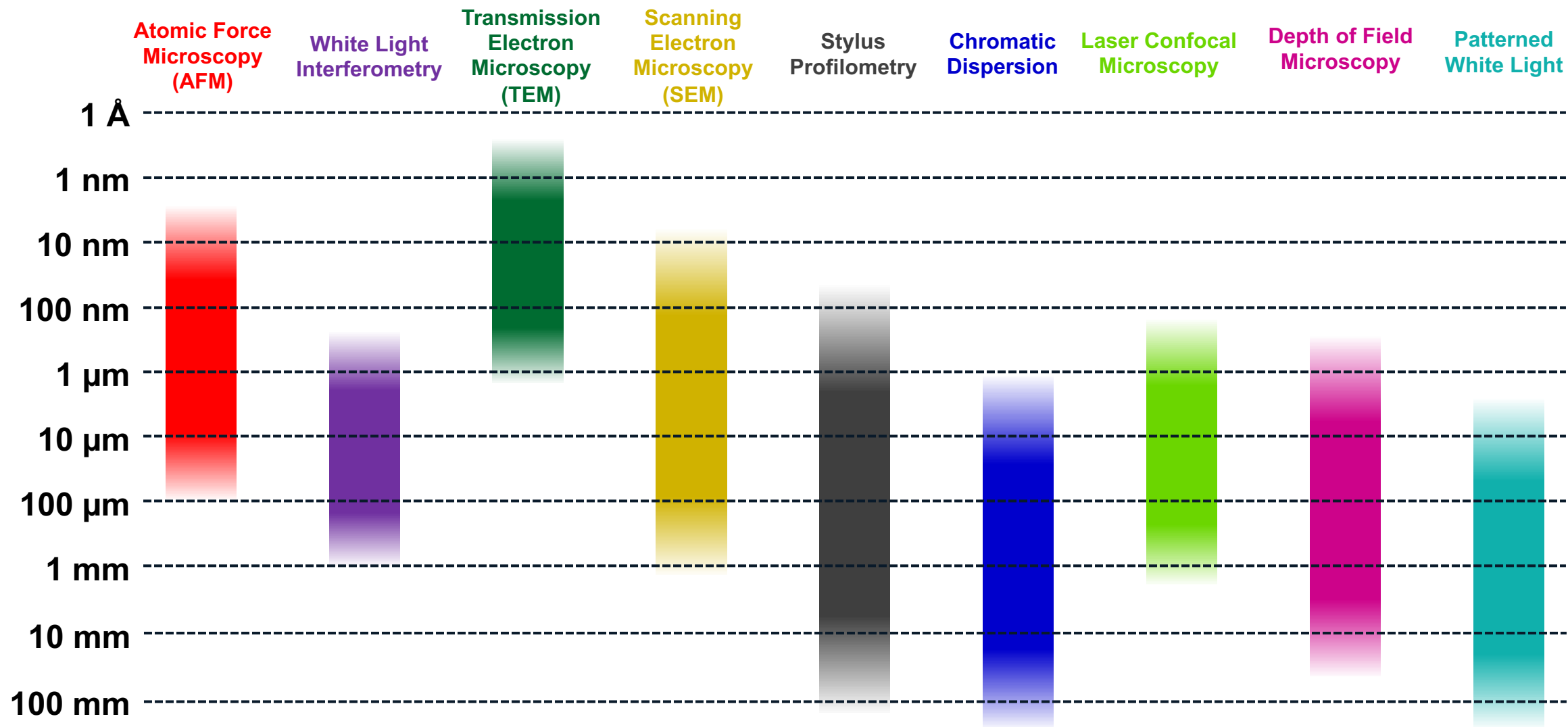




# Summary of 3 Part Series

## Roughness Scale (Horizontal Range)

38



# Summary of 3 Part Series Product Catalog

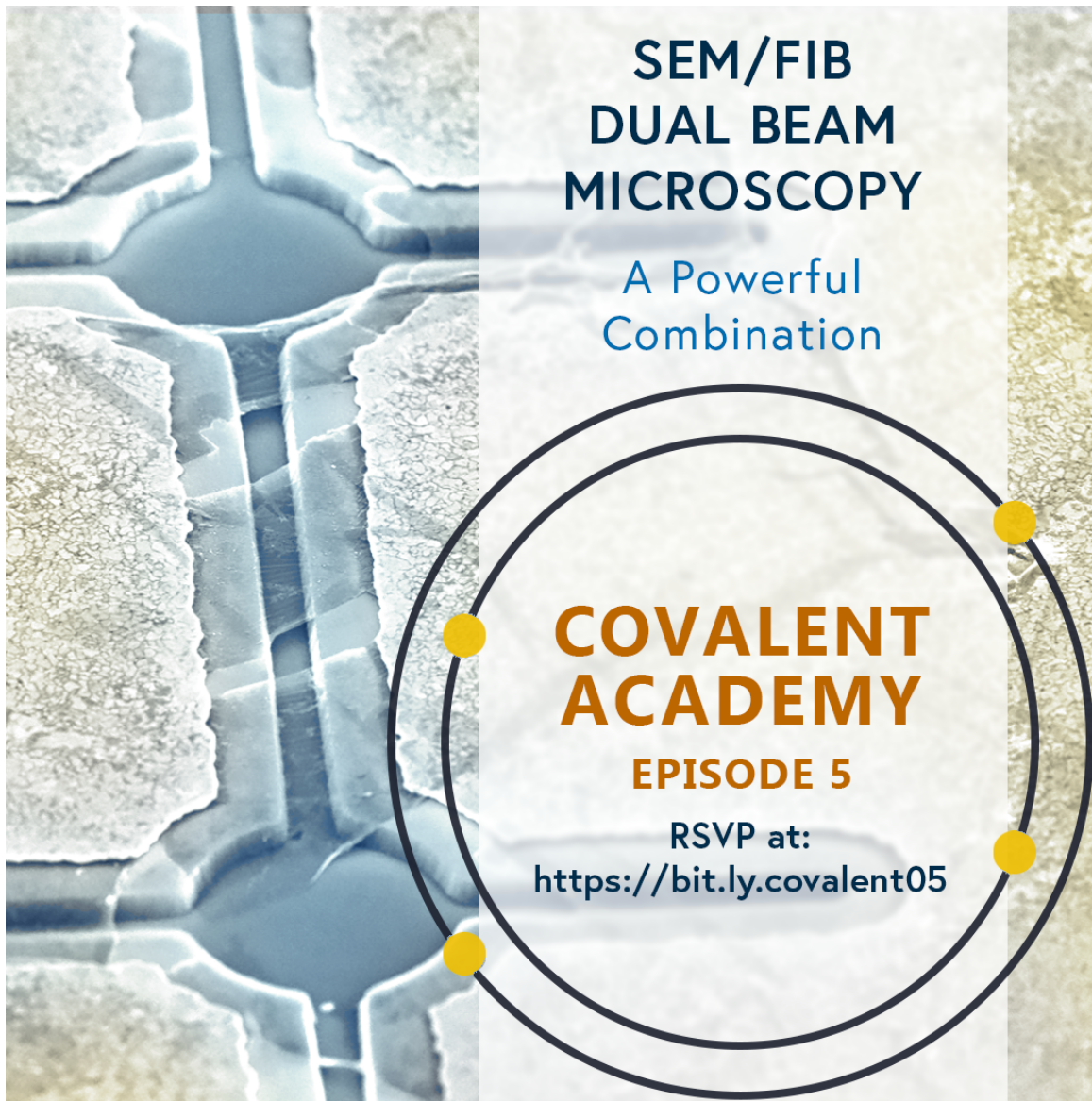
| Probe                             | "Stylus" Techniques                       |                                | Optical                              |                            |                                |                                     | Electron Beam                                    |                                  |
|-----------------------------------|-------------------------------------------|--------------------------------|--------------------------------------|----------------------------|--------------------------------|-------------------------------------|--------------------------------------------------|----------------------------------|
| Technique                         | Atomic Force Microscopy                   | Stylus Profilometry            | White Light Interferometry           | Laser Scanning Confocal    | Chromatic Confocal             | 3D White Light                      | Scanning Electron Microscopy                     | Transmission Electron Microscopy |
| You May Hear This Referred to As: | AFM or SPM                                | "Dektak"                       | Optical Profilometry                 | "Keyence"                  | "FRT"                          | "VR"                                | SEM or HRSEM                                     | TEM                              |
| Key Manufacturers                 | Bruker                                    | Bruker                         | Zygo                                 | <b>Keyence</b>             | FRT                            | <b>Keyence</b>                      | <b>ThermoFisher</b>                              | <b>ThermoFisher</b>              |
|                                   | Park Scientific                           | KLA                            | Bruker                               | Zeiss                      | Nanovea                        |                                     | JEOL                                             | JEOL                             |
|                                   | Asylum Research                           |                                | PolyTec                              | Leica                      |                                |                                     | Zeiss                                            | Hitachi                          |
|                                   | <b>Anton Paar</b>                         |                                |                                      | Olympus                    |                                |                                     | Hitachi                                          |                                  |
|                                   | Molecular Vista                           |                                |                                      | Nikon                      |                                |                                     | Tescan                                           |                                  |
|                                   | Many others                               |                                |                                      |                            |                                |                                     | Nikon                                            |                                  |
| Substrate Size Limitations        | 200mm max to reach edges; 300mm in center | Up to 300mm (Covalent @ 200mm) | Flexible, with fixtures              | Flexible, with fixtures    | Up to 300mm (Covalent @ 200mm) | Flexible, with fixtures             | Most analytical services <200mm                  | Coupons                          |
| Field of View - Min to Max        | 200nm to 70µm                             | Not Applicable                 | 160µm to 800µm                       | 100µm to 1mm               | Few um to 200mm                | 4mm to 24mm                         | 1µm to 2mm                                       | 2nm to 10µm                      |
| Vertical Resolution               | Å                                         | nm                             | Å                                    | nm                         | nm                             | Generally 3-5µm                     | nm                                               | Å                                |
| Particular challenges             | Sample should be smooth                   | No mapping                     | Reflectivity, +/- vertical ambiguity | Reflectivity, Steep Slopes | Steep Slopes                   | Resolution, shadowing, reflectivity | Non-conductive samples charging                  | Very small field of view         |
| Cost @ Covalent                   | \$175 / scan                              | \$225 / hr                     | \$275 / hr                           | \$300 / hr                 | \$300 / hr                     | \$275 / hr                          | \$275 / hr (standard res)<br>\$375 / hr (hi-res) | \$900 / sample (standard sample) |

| AFM Modes                            | Samples                    | Typical Data                                     |
|--------------------------------------|----------------------------|--------------------------------------------------|
| Contact AFM                          | Surface roughness          | Ra, Rq                                           |
| Tapping Mode AFM                     | Surface roughness          | Ra, Rq, Phase imaging                            |
| E-AFM (Electrostatic)                | Metal/Semiconductor films  | Electrostatic Potential                          |
| MFM (Magnetic)                       | Magnetic films             | Magnetic Domain Structure                        |
| Peak Force AFM                       | Thin films                 | Roughness, Surface Topography.                   |
| PF-QNM (Quantitative Nanomechanical) | Polymer coatings           | Roughness, Surface Topography, Polymer Domains   |
| AM-KPFM (Kevin-Probe, Amplitude Mod) | Thin films, semiconductors | Surface Potential                                |
| PFM (Piezo)                          | Piezo materials            | Piezo Domain Structure                           |
| SCM (Scanning Capacitance)           | Semiconductor films        | Dopant profile, Relative Capacitance             |
| FM-KPFM (Kevin-Probe, Frequency Mod) | Thin films, semiconductors | Surface Potential                                |
| Force Modulation                     | Polymer blends             | Relative Hardness of Viscoelastic Materials      |
| Conductive AFM                       | Thin films, thin oxide     | Leakage Currents, Variations in Conductivity     |
| TUNA (Tunneling)                     | Thin films, thin oxide     | Low Leakage Currents, Variations in Conductivity |
| PF-TUNA (Tunneling)                  | Thin films, thin oxide     | Low Leakage Currents, Variations in Conductivity |
| SSRM (Scanning Spreading Resistance) | Semiconductor films        | Dopant profile, Relative Resistance              |

- Many advanced AFM modes – surface property information other than topography/roughness.
- These techniques will be discussed in a later webinar.

- Michael Current, *Michael Current Scientific*.
- Nicholas Schacher, *NanoAndMore*.
- Patrick O'Hara, *Anton Paar*.
- Maxwell Junda, *Covalent Metrology*.
- Matt Wong, *Covalent Metrology*.



A scanning electron micrograph (SEM) showing a complex, multi-layered structure with various textures and colors, including blue, grey, and yellow. The structure appears to be a cross-section of a material with different layers and features.

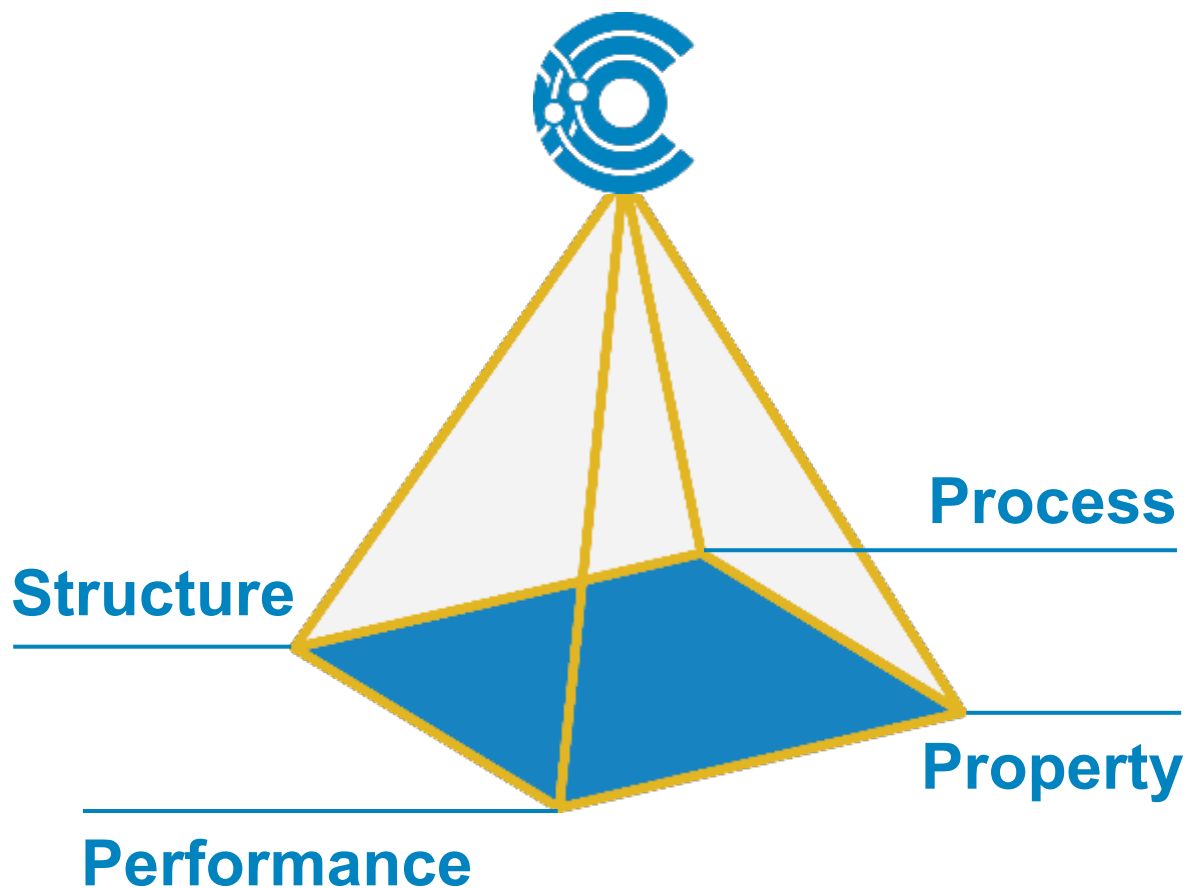
**SEM/FIB  
DUAL BEAM  
MICROSCOPY**

A Powerful  
Combination

**COVALENT  
ACADEMY**

**EPISODE 5**

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